(3)

Access DB# 163225

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Sin J. Lee Examiner #: 76060 Date: 8-11-2005
Art Unit: 1752 Phone Number 30 2-1333 Serial Number: 10/743,441
Mail Box and Bldg/Room Location: 9D60 (Rem.) Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

****

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Plz. see B.b.

Inventors (please provide full names): _____

Earliest Priority Filing Date: _____

SCIENTIFIC REFERENCE BR
Sci. & Tech. Inf. Ctr.
AUG
Pat. & T.M. Office

For Sequence Searches Only Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

Please search for a polymer having a [redacted] repeat unit (A')
shown in Cl. #2

****

STAFF USE ONLY

Searcher: Mike
Searcher Phone #: _____
Searcher Location: _____
Date Searcher Picked Up: 9/9/05
Date Completed: 9/9/05
Searcher Prep & Review Time: 40
Clerical Prep Time: 30
Online Time: 120

Type of Search

NA Sequence (#) _____
AA Sequence (#) _____
Structure (#) _____
Bibliographic _____
Litigation _____
Fulltext _____
Patent Family _____
Other _____

Vendors and cost where applicable

STN 9/9/17.17
Dialog _____
Questel/Orbit _____
Dr.Link _____
Lexis/Nexis _____
Sequence Systems _____
WWW/Internet _____
Other (specify) _____

PTO-1590 (8-01)

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=> fil reg
FILE 'REGISTRY' ENTERED AT 15:07:55 ON 09 SEP 2005

=> d his

     FILE 'HCAPLUS' ENTERED AT 13:05:34 ON 09 SEP 2005
L1            0 S US20040137366/PN

     FILE 'WPIX' ENTERED AT 13:07:14 ON 09 SEP 2005
L2            1 S L1

     FILE 'HCAPLUS' ENTERED AT 13:08:57 ON 09 SEP 2005
L3           73 S KAWAUCHI I?/AU
L4         1892 S NAKAMURA I?/AU
L5         1705 S TSUCHIYA M?/AU
L6            4 S L3 AND L4 AND L5
L7            1 S L6 AND HEAT?
L8            4 S L6 AND LITHOGRA?
                SEL RN

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L9           86 S E1-E86

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L14          23 S L13 AND L11
L15        3527 S L13 AND L11 FUL
                SAV L15 LEE441/A

     FILE 'HCAPLUS' ENTERED AT 14:03:47 ON 09 SEP 2005
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                E LITHOGRAPH
L17         195 S L16(L)LITHOGRAPH?
L18          15 S L17 AND HEAT(A)SENSITIV?
L19          19 S L17 AND PRECURSOR?
L20          31 S L18 OR L19

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L13             STR
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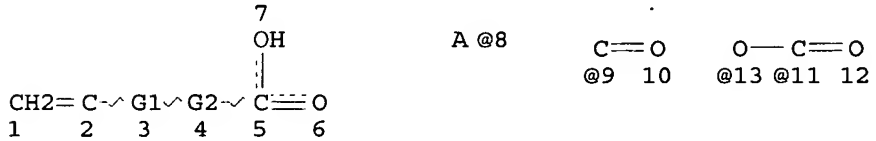


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DEFAULT MLEVEL IS ATOM
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DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
RING(S) ARE ISOLATED OR EMBEDDED
NUMBER OF NODES IS 13

STEREO ATTRIBUTES: NONE
L15 3527 SEA FILE=REGISTRY SSS FUL L13 AND L11
L16 2417 SEA FILE=HCAPLUS ABB=ON PLU=ON L15

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FILE 'HCAPLUS' ENTERED AT 15:08:18 ON 09 SEP 2005

=> d l20 1-31 ibib abs hitstr hitind

L20 ANSWER 1 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2005:303261 HCAPLUS
DOCUMENT NUMBER: 142:382218
TITLE: Lithographic printing plate **precursor** and lithographic printing method
INVENTOR(S): Makino, Naonori; Inno, Toshifumi; Yamasaki, Sumiaki
PATENT ASSIGNEE(S): Japan
SOURCE: U.S. Pat. Appl. Publ., 35 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

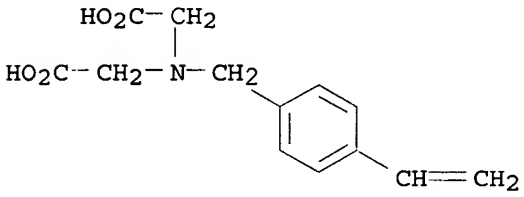
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005074692	A1	20050407	US 2004-951700	2004 0929
JP 2005125749	A2	20050519	JP 2004-265735	2004 0913
PRIORITY APPLN. INFO.:			JP 2003-339391 A	2003 0930

AB A lithog. printing plate **precursor** comprises: a support; and at least one layer comprising an image-recording layer, the image-recording layer comprising (A) an IR absorber, (B) a polymerization initiator, (C) a polymerizable compound, and (D) a binder polymer, wherein the image recording layer is capable of being removed with at least one of a printing ink and a fountain solution, wherein at least one of said at least one layer comprises a copolymer having (a1) a unit comprising at least one ethylenically unsatd. bond, and (a2) a unit comprising at least one functional group interacting with a surface of the support. And a lithog. printing method in which the lithog. printing plate **precursor** is used. The copolymer preferably has a hydrophilic segment. The copolymer preferably is contained in an undercoat layer formed between the support and the image-recording layer.

IT **194715-96-3P 849467-38-5P 849467-41-0P**
849467-48-7P 849467-49-8P 849467-50-1P
(**lithog.** printing plate **precursor** containing)
RN 194715-96-3 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-[(4-ethenylphenyl)methyl]-, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) (9CI) (CA INDEX NAME)

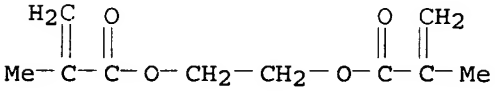
CM 1

CRN 46917-20-8
CMF C13 H15 N O4



CM 2

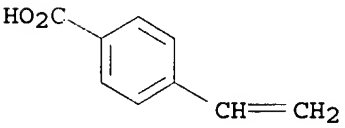
CRN 97-90-5
CMF C10 H14 O4



RN 849467-38-5 HCAPLUS
CN Benzoic acid, 4-ethenyl-, sodium salt, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) (9CI) (CA INDEX NAME)

CM 1

CRN 77124-40-4
CMF C9 H8 O2 . Na

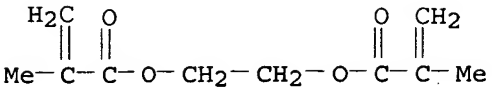


● Na

CM 2

CRN 97-90-5

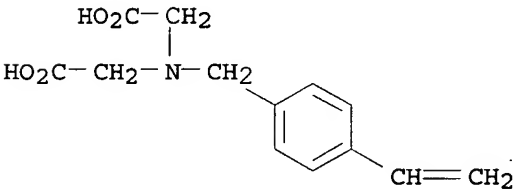
CMF C10 H14 O4



RN 849467-41-0 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-[(4-ethenylphenyl)methyl]-, disodium salt, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) (9CI) (CA INDEX NAME)

CM 1

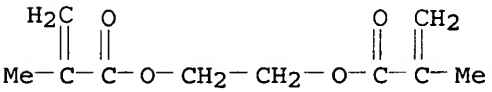
CRN 68517-06-6
CMF C13 H15 N O4 . 2 Na



●2 Na

CM 2

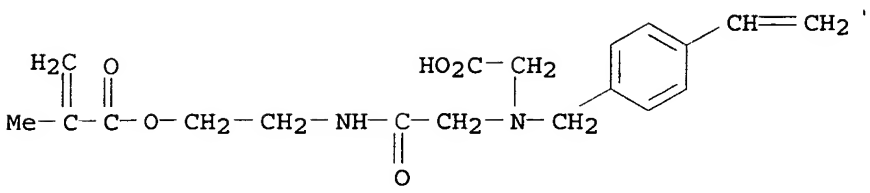
CRN 97-90-5
CMF C10 H14 O4



RN 849467-48-7 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-[(4-ethenylphenyl)methyl]-, disodium salt, polymer with 2-[[[(carboxymethyl)[(4-ethenylphenyl)methyl]amino]acetyl]amino]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

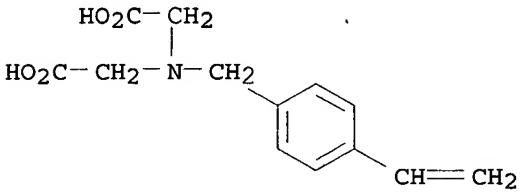
CM 1

CRN 849467-47-6
CMF C19 H24 N2 O5



CM 2

CRN 68517-06-6
CMF C13 H15 N O4 . 2 Na

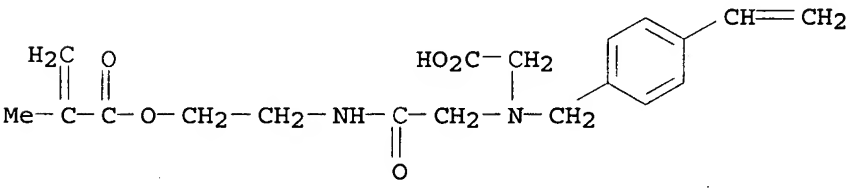


●2 Na

RN 849467-49-8 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-[(4-ethenylphenyl)methyl]-, polymer with 2-[[[(carboxymethyl)[(4-ethenylphenyl)methyl]amino]acetyl]amino]ethyl 2-methyl-2-propenoate and N-(1-methylethyl)-2-propenamide (9CI) (CA INDEX NAME)

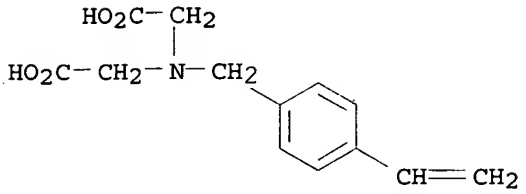
CM 1

CRN 849467-47-6
CMF C19 H24 N2 O5



CM 2

CRN 46917-20-8
CMF C13 H15 N O4



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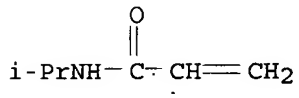
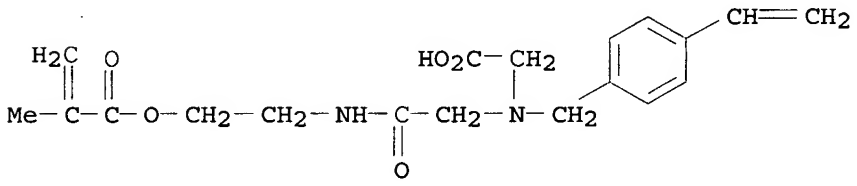
CRN 2210-25-5
CMF C6 H11 N O



RN 849467-50-1 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-[(4-ethenylphenyl)methyl]-, polymer with 2-[[[(carboxymethyl)[(4-ethenylphenyl)methyl]amino]acetyl]amino]ethyl 2-methyl-2-propenoate and 2-methyl-2-[(1-oxo-2-propenyl)amino]-1-propanesulfonic acid monosodium salt (9CI) (CA INDEX NAME)

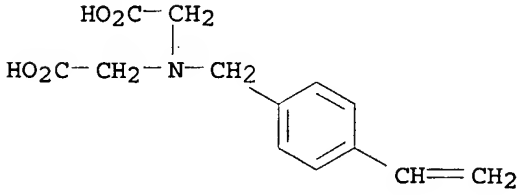
CM 1

CRN 849467-47-6
CMF C19 H24 N2 O5



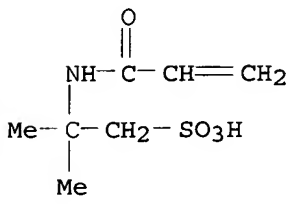
CM 2

CRN 46917-20-8
CMF C13 H15 N O4



CM 3

CRN 5165-97-9
CMF C7 H13 N O4 S . Na



● Na

IC ICM G03C001-76
INCL 430270100
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38
ST lithog printing plate **precursor**
IT Optical materials
(IR absorbers; lithog. printing plate **precursor** and lithog. printing method)
IT IR materials
(absorbers; lithog. printing plate **precursor** and lithog. printing method)
IT Lithographic plates
(lithog. printing plate **precursor** and lithog. printing method)
IT 83176-82-3P 93441-11-3P **194715-96-3P**
849467-38-5P 849467-39-6P 849467-40-9P
849467-41-0P 849467-43-2P 849467-44-3P 849467-45-4P
849467-46-5P **849467-48-7P 849467-49-8P**
849467-50-1P 849467-51-2P 849467-52-3P 849467-53-4P
849467-54-5P 849467-55-6P
(**lithog.** printing plate **precursor** containing)

L20 ANSWER 2 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2005:215777 HCAPLUS
DOCUMENT NUMBER: 142:269282
TITLE: **Heat-sensitive** lithographic printing master plates for development-free CTP (computer-to-plate) system with improved wear resistance
INVENTOR(S): Yamazaki, Sumiaki; Aoshima, Norio
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 32 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE

JP 2005059378	A2	20050310	JP 2003-292225	2003 0812

PRIORITY APPLN. INFO.: JP 2003-292225 2003 0812

AB The plates have ink-receiving layers (A) containing polymers bearing cationic groups, groups including 2 carbonyls linked via 1 of C or N atom, and/or lactone groups, hydrophilic layers (B) containing colloidal particles of oxides or hydroxides of Be, Mg, Al, Si, Ti, B, Ge, Sn, Zr, Ir, V, Sb, and/or transition metals, and optionally hydrophilic overcoat layers (C, removable on printers) in this order on supports, wherein A, B, and/or C contain light-heat converting agents.

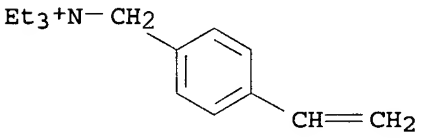
IT **220227-02-1**
(binder, ink-receiving layer; **heat-sensitive lithog.** printing plates with good wear resistance for development-free CTP system)

RN 220227-02-1 HCAPLUS

CN Benzenemethanaminium, 4-ethenyl-N,N,N-triethyl-, chloride, polymer with 4-ethenylbenzoic acid (9CI) (CA INDEX NAME)

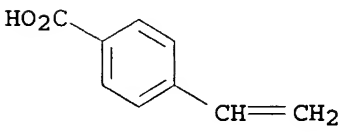
CM 1

CRN 14350-43-7
CMF C15 H24 N . Cl



CM 2

CRN 1075-49-6
CMF C9 H8 O2



IC ICM B41N001-14
ICS G03F007-00; G03F007-004; G03F007-11

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and

Other Reprographic Processes)
Section cross-reference(s): 38

ST lithog plate oxide hydrophilic coating CTP; **heat sensitive** printing plate IR absorber; wear resistance cationic polymer ink receiver

IT Optical materials
(IR absorbers; **heat-sensitive** lithog. printing plates with good wear resistance for development-free CTP system)

IT IR materials
(absorbers; **heat-sensitive** lithog. printing plates with good wear resistance for development-free CTP system)

IT Polymers, uses
(bearing cationic, dicarbonyl, or lactone groups, binder, ink-receiving layer; **heat-sensitive** lithog. printing plates with good wear resistance for development-free CTP system)

IT Hydroxides (inorganic)
Oxides (inorganic), uses
(colloidal particle, hydrophilic layer; **heat-sensitive** lithog. printing plates with good wear resistance for development-free CTP system)

IT Lithographic plates
(**heat-sensitive** lithog. printing plates with good wear resistance for development-free CTP system)

IT Colloids
(hydrophilic layer; **heat-sensitive** lithog. printing plates with good wear resistance for development-free CTP system)

IT Silica gel, uses
(hydrophilic layer; **heat-sensitive** lithog. printing plates with good wear resistance for development-free CTP system)

IT 134127-48-3
(IR absorber, ink-receiving layer; **heat-sensitive** lithog. printing plates with good wear resistance for development-free CTP system)

IT 27901-88-8 **220227-02-1** 845867-51-8 845867-52-9 845867-53-0 845867-54-1 845867-55-2
(binder, ink-receiving layer; **heat-sensitive lithog.** printing plates with good wear resistance for development-free CTP system)

IT 9000-01-5, Arabic gum
(binder, overcoat layer; **heat-sensitive** lithog. printing plates with good wear resistance for development-free CTP system)

IT 7631-86-9, Silica, uses
(colloidal particle, hydrophilic layer; **heat-sensitive** lithog. printing plates with good wear resistance for development-free CTP system)

IT 9003-01-4, Acrylic acid polymer
(hydrophilic layer; **heat-sensitive** lithog. printing plates with good wear resistance for development-free CTP system)

IT 37321-70-3, JIS A 1050
(support; **heat-sensitive** lithog. printing plates with good wear resistance for development-free CTP system)

L20 ANSWER 3 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2005:122676 HCAPLUS
DOCUMENT NUMBER: 142:228751
TITLE: Radical polymerizable composition and lithographic printing plate **precursor** using the same
INVENTOR(S): Kakino, Ryuki; Kunita, Kazuto
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: U.S. Pat. Appl. Publ., 45 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005031986	A1	20050210	US 2004-900169	20040728
JP 2005062856	A2	20050310	JP 2004-220626	20040728

PRIORITY APPLN. INFO.: JP 2003-202332 A 20030728

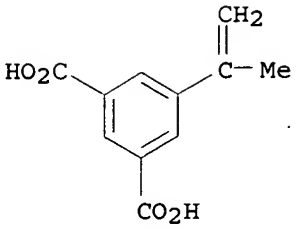
AB A radical polymerizable composition comprises (A) an alkali-soluble resin containing a radical polymerizable group, (B) a radical polymerizable compound, and (C) a radical initiator, wherein reactivity of a polymerizable group of the polymerizable compound (B) to a polymerizable group of the polymerizable compound (B) is larger than reactivity of a polymerizable group of the polymerizable compound (B) to a radical polymerizable group of the alkali-soluble resin (A), and a reactivity of a radical polymerizable group of the alkali-soluble resin (A) to a polymerizable group of the polymerizable compound (B) is larger than reactivity of a radical polymerizable group of the alkali-soluble resin (A) to a radical polymerizable group of the alkali-soluble resin (A).

IT **840488-60-0P**
(radical polymerizable composition for **lithog.** printing plate **precursor** containing)

RN 840488-60-0 HCAPLUS
CN 1,3-Benzenedicarboxylic acid, 5-(1-methylethenyl)-, polymer with (4-ethenylphenyl)methyl 2-methyl-2-propenoate and 1-methylethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

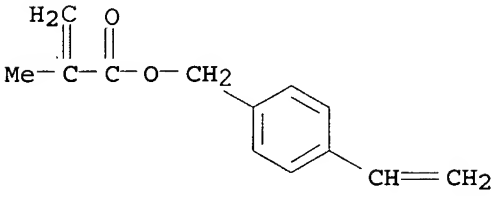
CM 1

CRN 840488-59-7
CMF C11 H10 O4



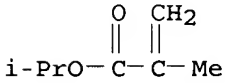
CM 2

CRN 99413-45-3
CMF C13 H14 O2



CM 3

CRN 4655-34-9
CMF C7 H12 O2



IC ICM G03C001-76
INCL 430270100
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38
ST radical polymerizable compn lithog printing plate **precursor**
IT Lithographic plates
(radical polymerizable composition and lithog. printing plate **precursor** using same)
IT 840488-52-0P 840488-53-1P 840488-54-2P 840488-55-3P 840488-56-4P 840488-57-5P 840488-58-6P **840488-60-0P** 840488-61-1P
(radical polymerizable composition for **lithog.** printing plate **precursor** containing)
IT 1985-51-9 3290-92-4 29570-58-9 79559-96-9 158464-09-6
(radical polymerizable composition for lithog. printing plate **precursor** containing)

L20 ANSWER 4 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:1080080 HCAPLUS

DOCUMENT NUMBER: 142:65347
TITLE: **Heat-sensitive** positive-working lithographic printing plate **precursors**
INVENTOR(S): Sasaki, Hideto
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 40 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004354905	A2	20041216	JP 2003-155257	2003 0530

PRIORITY APPLN. INFO.: JP 2003-155257 2003 0530

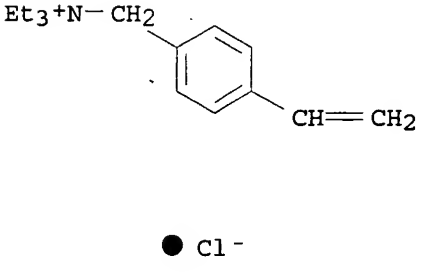
AB The title **precursor** has an intermediate layer containing a polymer and an image-recording layer, which increases the solubility towards an alkaline solution by heat, on an aluminum support, which is roughened, anodized, and treated with alkali metal silicate, wherein the anodization provides 3-8 μm average pore size in the formed surface layer, wherein the support has 1-10 mg/m2 of fixed Si on the surface, and wherein the intermediate layer is made of 10-40 mg/m2 coating. The **precursor** shows good development properties and provides printing plate of high printing durability.

IT **220227-02-1**, 4-Vinylbenzoic acid-Triethyl(p-vinylbenzyl)ammonium chloride copolymer
(intermediate layer; **heat-sensitive** pos.-working **lithog.** printing plate **precursors**)

RN 220227-02-1 HCAPLUS
CN Benzenemethanaminium, 4-ethenyl-N,N,N-triethyl-, chloride, polymer with 4-ethenylbenzoic acid (9CI) (CA INDEX NAME)

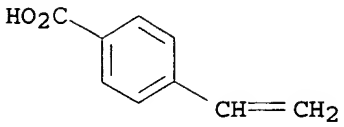
CM 1

CRN 14350-43-7
CMF C15 H24 N . Cl



CM 2

CRN 1075-49-6
CMF C9 H8 O2



IC ICM G03F007-11
ICS G03F007-00; G03F007-09
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST heat pos lithog printing plate **precursor** support intermediate layer
IT Anodization
Surface roughness
(**heat-sensitive** pos.-working lithog. printing plate **precursors**)
IT Lithographic plates
(**precursors**, **heat-sensitive**, pos.-working; **heat-sensitive** pos.-working lithog. printing plate **precursors**)
IT 12627-13-3D, Silicate, alkali metal
(**heat-sensitive** pos.-working lithog. printing plate **precursors**)
IT **220227-02-1**, 4-Vinylbenzoic acid-Triethyl(p-vinylbenzyl)ammonium chloride copolymer
(intermediate layer; **heat-sensitive** pos.-working **lithog.** printing plate **precursors**)
IT 39364-62-0
(support; **heat-sensitive** pos.-working lithog. printing plate **precursors**)

L20 ANSWER 5 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:1076959 HCAPLUS
DOCUMENT NUMBER: 142:65344
TITLE: **Heat-sensitive** positive-working lithographic printing plate **precursors**
INVENTOR(S): Sasaki, Hideto
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 35 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004354918	A2	20041216	JP 2003-155431	2003

0530

PRIORITY APPLN. INFO.: JP 2003-155431

2003
0530

AB The title **precursor** has an intermediate layer containing a polymer and an image-recording layer, which increases solubility towards an alkaline solution by heat, on an aluminum support, wherein the intermediate layer has ≥50 % surface carbon concentration by X-ray electron spectroscopy anal. and wherein the support has ≥6 mg/m2 absorption of the polymer used for the intermediate layer by dipped in 5 % polymer in MeOH solution at 25° C for 300 s and washed with methanol. The **precursor** shows good development properties and provides printing plate of high printing durability.

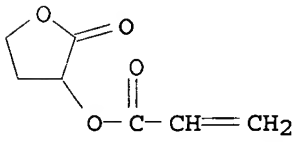
IT **808143-96-6**, Triethyl(p-vinylbenzyl)ammonium chloride-4-vinylbenzoic acid-2-Propenoic acid, tetrahydro-2-oxo-3-furanyl ester copolymer
(intermediate layer; **heat-sensitive** pos.-working **lithog.** printing plate **precursors**)

RN 808143-96-6 HCAPLUS

CN Benzenemethanaminium, 4-ethenyl-N,N,N-triethyl-, chloride, polymer with 4-ethenylbenzoic acid and tetrahydro-2-oxo-3-furanyl 2-propenoate (9CI) (CA INDEX NAME)

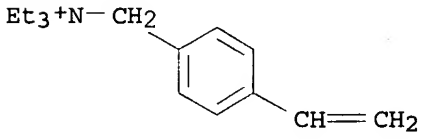
CM 1

CRN 328249-37-2
CMF C7 H8 O4



CM 2

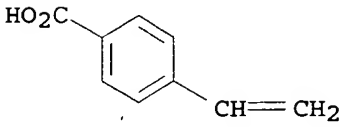
CRN 14350-43-7
CMF C15 H24 N . Cl



● Cl^-

CM 3

CRN 1075-49-6
CMF C9 H8 O2



IC ICM G03F007-11
ICS G03F007-00; G03F007-004
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST heat pos lithog printing plate **precursor** support intermediate layer
IT Lithographic plates
(**precursors**, **heat-sensitive**, pos.-working; **heat-sensitive** pos.-working lithog. printing plate **precursors**)
IT **808143-96-6**, Triethyl(p-vinylbenzyl)ammonium chloride-4-vinylbenzoic acid-2-Propenoic acid, tetrahydro-2-oxo-3-furanyl ester copolymer
(intermediate layer; **heat-sensitive** pos.-working **lithog.** printing plate **precursors**)
IT 7429-90-5, Aluminum, uses
(support; **heat-sensitive** pos.-working lithog. printing plate **precursors**)

L20 ANSWER 6 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:1038492 HCAPLUS
DOCUMENT NUMBER: 142:45928
TITLE: Presensitized positive-working lithographic plate master showing excellent printability as well as smear resistance
INVENTOR(S): Takahashi, Miki; Sasaki, Hideto; Hotta, Hisashi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 51 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004341141	A2	20041202	JP 2003-136545	2003 0514
PRIORITY APPLN. INFO.:			JP 2003-136545	2003 0514

AB The title lithog. plate master includes an intermediate layer interposed between a hydrophilic support and a pos.-working

heat-sensitive layer, wherein the intermediate layer contains a compound capable of interacting to a water-insol. alkali-soluble polymer. The compound is a polymer having a functional side chain(s) selected from -Y-Ar, -Y-(CnH2nO)m-R1, -Y-CO-NR3R2, and -Y-NR5-CO-R4 [Y = single bond, connection group; Ar = N-containing heteroaryl; R1-5 = H, C1-30-hydrocarbyl; m = 1-100; n ≥2].

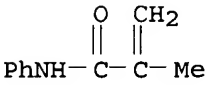
IT **604813-21-0 803729-44-4**
(in intermediate layer of presensitized pos.-working **lithog.** plate master showing excellent printability as well as smear resistance)

RN 604813-21-0 HCAPLUS

CN Benzoic acid, 4-ethenyl-, polymer with 2-methyl-N-phenyl-2-propenamide (9CI) (CA INDEX NAME)

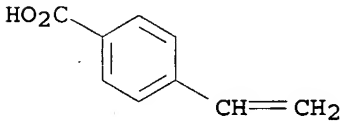
CM 1

CRN 1611-83-2
CMF C10 H11 N O



CM 2

CRN 1075-49-6
CMF C9 H8 O2

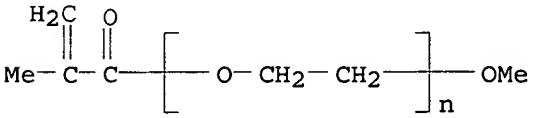


RN 803729-44-4 HCAPLUS

CN Benzoic acid, 4-ethenyl-, polymer with α-(2-methyl-1-oxo-2-propenyl)-ω-methoxypoly(oxy-1,2-ethanediyl) (9CI) (CA INDEX NAME)

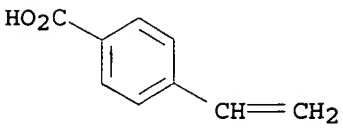
CM 1

CRN 26915-72-0
CMF (C2 H4 O)n C5 H8 O2
CCI PMS



CM 2

CRN 1075-49-6
CMF C9 H8 O2



IC ICM G03F007-11
ICS G03F007-00; G03F007-004
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT 9003-39-8 25232-41-1 28062-44-4 **604813-21-0**
803729-44-4 803729-45-5
(in intermediate layer of presensitized pos.-working **lithog.** plate master showing excellent printability as well as smear resistance)

L20 ANSWER 7 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:876832 HCAPLUS
DOCUMENT NUMBER: 141:372803
TITLE: Positive-working lithographic printing master plate having graft copolymer interlayer on support
INVENTOR(S): Tashiro, Hiroshi; Takahashi, Miki; Hotta, Hisashi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 38 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004294908	A2	20041021	JP 2003-89094	2003 0327

PRIORITY APPLN. INFO.: JP 2003-89094 2003 0327

AB Disclosed is the pos.-working lithog. printing master comprising on a support a graft copolymer interlayer, a water-soluble lower layer containing an alkali-soluble resin, and a water-soluble upper **heat-sensitive** layer containing an alkali-soluble resin and an IR-absorbing dye in the order. The use of the interlayer provided excellent sensitivity, development latitude, and printing durability.
IT **777948-09-1P**, p-Vinylbenzoic acid-glycidyl methacrylate-vinylbenzyltriethylammonium chloride graft copolymer
777948-10-4P, p-VinylBenzoic acid-glycidyl methacrylate-α-methacryloyloxy-γ-butyrolactone graft copolymer
(pos.-working **lithog.** printing master plate having

graft copolymer interlayer on support)

RN 777948-09-1 HCAPLUS

CN Benzenemethanaminium, ar-ethenyl-N,N,N-triethyl-, polymer with 4-ethenylbenzoic acid and oxiranylmethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

CM 1

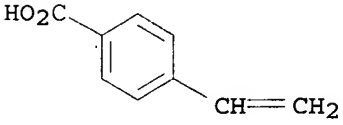
CRN 112708-38-0
CMF C15 H24 N
CCI IDS

D1— CH═ CH_2

$Et_3{}^+N$— CH_2— D1

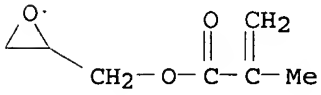
CM 2

CRN 1075-49-6
CMF C9 H8 O2



CM 3

CRN 106-91-2
CMF C7 H10 O3



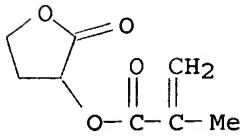
RN 777948-10-4 HCAPLUS

CN Benzoic acid, 4-ethenyl-, polymer with oxiranylmethyl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

CM 1

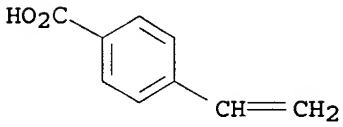
CRN 195000-66-9

CMF C8 H10 O4



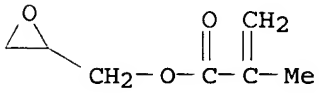
CM 2

CRN 1075-49-6
CMF C9 H8 O2



CM 3

CRN 106-91-2
CMF C7 H10 O3



IC ICM G03F007-11
ICS G03F007-00; G03F007-004
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38
IT **777948-09-1P**, p-Vinylbenzoic acid-glycidyl methacrylate-vinylbenzyltriethylammonium chloride graft copolymer
777948-10-4P, p-VinylBenzoic acid-glycidyl methacrylate-α-methacryloyloxy-γ-butyrolactone graft copolymer
(pos.-working **lithog.** printing master plate having graft copolymer interlayer on support)

L20 ANSWER 8 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:871271 HCAPLUS
DOCUMENT NUMBER: 141:372783
TITLE: Positive-working lithographic printing master plate having lactone-based polymer interlayer on support
INVENTOR(S): Tashiro, Hiroshi; Takahashi, Miki; Hotta, Hisashi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 39 pp.
CODEN: JKXXAF

DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004294909	A2	20041021	JP 2003-89095	2003 0327

PRIORITY APPLN. INFO.: JP 2003-89095 2003 0327

AB Disclosed is the pos.-working lithog. printing master comprising on a support an interlayer made from a lactone-based polymer, a water-soluble lower layer containing an alkali-soluble resin, and a water-soluble upper **heat-sensitive** layer containing an alkali-soluble resin and an IR-absorbing dye in the order. The use of the interlayer provided excellent sensitivity, development latitude, and printing durability.

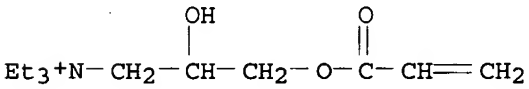
IT **777947-84-9**
(pos.-working **lithog.** printing master plate having lactone-based polymer interlayer on support)

RN 777947-84-9 HCAPLUS

CN 1-Propanaminium, N,N,N-triethyl-2-hydroxy-3-[(1-oxo-2-propenyl)oxy]-, chloride, polymer with 4-ethenylbenzoic acid and tetrahydro-4,4-dimethyl-2-oxo-3-furanyl 2-propenoate (9CI) (CA INDEX NAME)

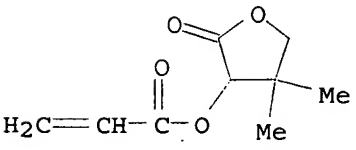
CM 1

CRN 777947-83-8
CMF C12 H24 N O3 . Cl



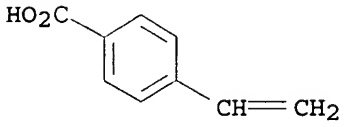
CM 2

CRN 84822-49-1
CMF C9 H12 O4



CM 3

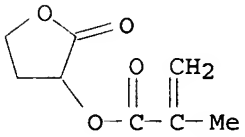
CRN 1075-49-6
CMF C9 H8 O2



IT **669013-38-1P**, α-Methacryloyloxy-γ-butyrolactone-p-vinylbenzoic acid copolymer
(pos.-working **lithog.** printing master plate having lactone-based polymer interlayer on support)
RN 669013-38-1 HCAPLUS
CN Benzoic acid, 4-ethenyl-, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

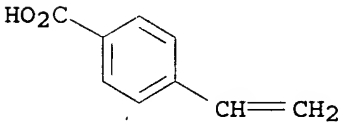
CM 1

CRN 195000-66-9
CMF C8 H10 O4



CM 2

CRN 1075-49-6
CMF C9 H8 O2



IC ICM G03F007-11
ICS G03F007-00; G03F007-004
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38
IT **777947-84-9**
(pos.-working **lithog.** printing master plate having lactone-based polymer interlayer on support)
IT **669013-38-1P**, α-Methacryloyloxy-γ-butyrolactone-p-vinylbenzoic acid copolymer

(pos.-working **lithog.** printing master plate having lactone-based polymer interlayer on support)

L20 ANSWER 9 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:801659 HCAPLUS
DOCUMENT NUMBER: 141:304335
TITLE: Original plate of lithographic printing plate
INVENTOR(S): Aogo, Toshiaki
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 28 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004272058	A2	20040930	JP 2003-64761	2003 0311

PRIORITY APPLN. INFO.: JP 2003-64761 2003 0311

OTHER SOURCE(S): MARPAT 141:304335

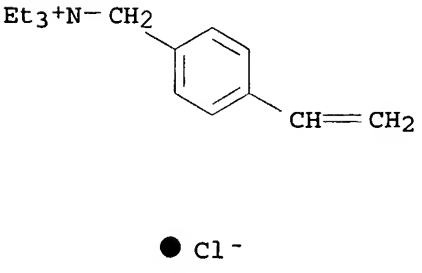
AB The invention is concerned about an original plate for making IR laser pos. lithog. printing plate using direct plate-making method. The plate comprises, on a support having a hydrophilic surface, a **heat-sensitive** layer containing (A) a water-insol. alkali soluble resin, (B) an IR-absorbing dye, and (C) a cyclodextrin derivative The **heat-sensitive** layer has an increased solubility in aqueous alkali solution upon IR exposure.

IT **220227-02-1**
(substrate surface coating; original plate of **lithog.** printing plate containing cyclodextrin derivs.)

RN 220227-02-1 HCAPLUS
CN Benzenemethanaminium, 4-ethenyl-N,N,N-triethyl-, chloride, polymer with 4-ethenylbenzoic acid (9CI) (CA INDEX NAME)

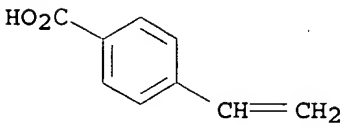
CM 1

CRN 14350-43-7
CMF C15 H24 N . Cl



CM 2

CRN 1075-49-6
CMF C9 H8 O2



IC ICM G03F007-004
ICS G03F007-00; G03F007-11
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT **220227-02-1**
(substrate surface coating; original plate of **lithog.** printing plate containing cyclodextrin derivs.)

L20 ANSWER 10 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:779269 HCAPLUS
DOCUMENT NUMBER: 141:285849
TITLE: IR-sensitive direct-imaging lithographic printing plate **precursors**
INVENTOR(S): Nagashima, Akira
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 29 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004264747	A2	20040924	JP 2003-57123	2003 0304
CN 1527137	A	20040908	CN 2003-10114267	2003 1112

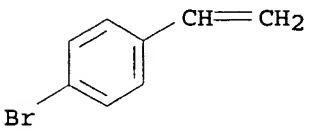
PRIORITY APPLN. INFO.: JP 2003-57123 A 2003 0304

AB The title printing plate **precursor** has an olefinic resin, a novolak resin, and a light-to-heat converting compound on a hydrophilized support, wherein the olefinic resin is a copolymer of H2C=C(-R1)(-X-COOH)(R1 = H, alkyl; X = arylene, -CO-Y-, -OCO-Y-, -Ar-Y-; Y = 2-valent connecting group; Ar = arylene) and (meth)acrylate, a (meth)acrylamide derivative, or a styrene derivative and wherein the surface of the support is electrochem. roughened in acidic solution mainly containing hydrogen chloride. The printing plate **precursor** shows wide development latitude and provides printing plate of high printing durability.
IT **604813-23-2**
(IR-sensitive direct-imaging **lithog.** printing plate

precursors)
RN 604813-23-2 HCAPLUS
CN Benzoic acid, 4-ethenyl-, polymer with 1-bromo-4-ethenylbenzene and N-(1,1-dimethylethyl)-2-propenamide (9CI) (CA INDEX NAME)

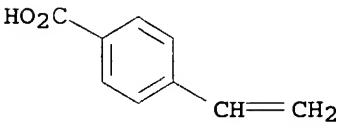
CM 1

CRN 2039-82-9
CMF C8 H7 Br



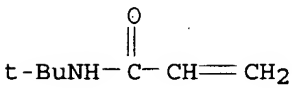
CM 2

CRN 1075-49-6
CMF C9 H8 O2



CM 3

CRN 107-58-4
CMF C7 H13 N O



IC ICM G03F007-033
ICS B41N001-08; B41N003-03; G03F007-004; G03F007-09
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35
ST IR lithog printing plate **precursor** support resin
IT Lithographic plates
(IR-sensitive direct-imaging lithog. printing plate **precursors**)
IT Phenolic resins, uses
(novolak; IR-sensitive direct-imaging lithog. printing plate **precursors**)
IT 7647-01-0, Hydrogen chloride, processes 27029-76-1
(IR-sensitive direct-imaging lithog. printing plate **precursors**)
IT **604813-23-2** 604813-56-1 604813-57-2 604813-62-9

604813-64-1 604813-65-2 604813-66-3 760965-90-0
(IR-sensitive direct-imaging **lithog.** printing plate **precursors**)
IT 1344-09-8, Sodium silicate
(hydrophilizing agent; IR-sensitive direct-imaging lithog. printing plate **precursors**)
IT 37321-70-3, JIS A1050
(support; IR-sensitive direct-imaging lithog. printing plate **precursors**)

L20 ANSWER 11 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:612321 HCAPLUS
DOCUMENT NUMBER: 141:148156
TITLE: Method for making lithographic printing plates by direct IR-imaging process
INVENTOR(S): Kawauchi, Ikuo; Nagase, Hiroyuki
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 37 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004212649	A2	20040729	JP 2002-382229	2002 1227
PRIORITY APPLN. INFO.:			JP 2002-382229	2002 1227

AB The title method includes the steps of: imagewise exposing a printing plate **precursor** having an image-forming layer on a support; and developing the image with an alkali developer, wherein the image-forming layer contains a copolymer of CH2=C(R)(-X-COOH) (R = H, alkyl; X = arylene) and wherein the developer contains an anionic surfactant having sulfonium groups. The method uses decreased exposure energy and generates little residue film in the development.
IT **188601-29-8P 604813-16-3P 604813-18-5P 604813-19-6P 604813-23-2P**
(copolymer; light-sensitive layer of **lithog.** printing plate **precursors**)
RN 188601-29-8 HCAPLUS
CN Benzoic acid, 4-ethenyl-, polymer with ethenylmethylbenzene (9CI) (CA INDEX NAME)

CM 1

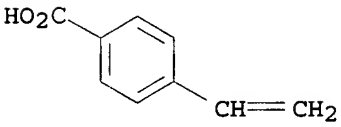
CRN 25013-15-4
CMF C9 H10
CCI IDS

D1— Me

D1— CH═ CH_2

CM 2

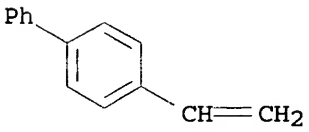
CRN 1075-49-6
CMF C9 H8 O2



RN 604813-16-3 HCAPLUS
CN Benzoic acid, 4-ethenyl-, polymer with 4-ethenyl-1,1'-biphenyl (9CI) (CA INDEX NAME)

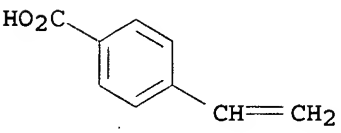
CM 1

CRN 2350-89-2
CMF C14 H12



CM 2

CRN 1075-49-6
CMF C9 H8 O2

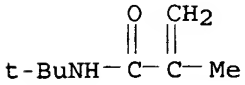


RN 604813-18-5 HCAPLUS

CN Benzoic acid, 4-ethenyl-, polymer with N-(1,1-dimethylethyl)-2-methyl-2-propenamide (9CI) (CA INDEX NAME)

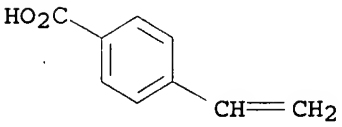
CM 1

CRN 6554-73-0
CMF C8 H15 N O



CM 2

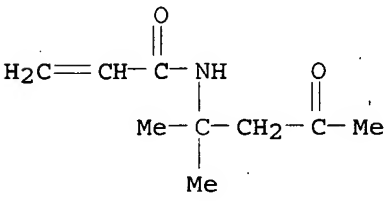
CRN 1075-49-6
CMF C9 H8 O2



RN 604813-19-6 HCAPLUS
CN Benzoic acid, 4-ethenyl-, polymer with N-(1,1-dimethyl-3-oxobutyl)-2-propenamide (9CI) (CA INDEX NAME)

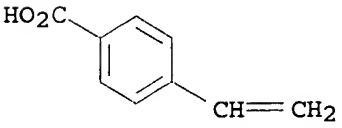
CM 1

CRN 2873-97-4
CMF C9 H15 N O2



CM 2

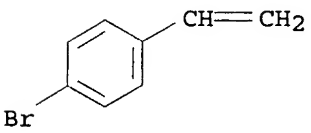
CRN 1075-49-6
CMF C9 H8 O2



RN 604813-23-2 HCAPLUS
CN Benzoic acid, 4-ethenyl-, polymer with 1-bromo-4-ethenylbenzene and N-(1,1-dimethylethyl)-2-propenamide (9CI) (CA INDEX NAME)

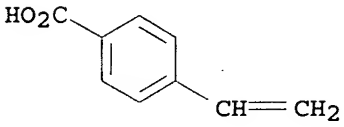
CM 1

CRN 2039-82-9
CMF C8 H7 Br



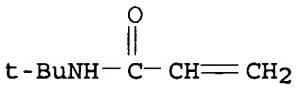
CM 2

CRN 1075-49-6
CMF C9 H8 O2



CM 3

CRN 107-58-4
CMF C7 H13 N O



IC ICM G03F007-00
ICS G03F007-033; G03F007-32
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 46
IT 146115-88-0P **188601-29-8P 604813-16-3P**
604813-18-5P 604813-19-6P 604813-23-2P
604813-38-9P 604813-40-3P 604813-41-4P 604813-42-5P
604813-43-6P 604813-44-7P 604813-45-8P 604813-46-9P
604813-47-0P 604813-48-1P 604813-50-5P 604813-52-7P
604813-54-9P 604813-55-0P 604813-56-1P 604813-57-2P
604813-59-4P 604813-60-7P 604813-61-8P 604813-62-9P
604813-64-1P 604813-65-2P 604813-66-3P 604813-67-4P
722484-52-8P 722494-08-8P 722494-09-9P
(copolymer; light-sensitive layer of **lithog.** printing plate **precursors**)

L20 ANSWER 12 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:569739 HCAPLUS
DOCUMENT NUMBER: 141:131306
TITLE: Infrared-sensitive lithographic printing plate
INVENTOR(S): Kawauchi, Ikuo; Nakamura, Ippei
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: U.S. Pat. Appl. Publ., 25 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2004137365	A1	20040715	US 2003-743412	2003 1223
JP 2004212650	A2	20040729	JP 2002-382230	2002 1227
EP 1433595	A2	20040630	EP 2003-29286	2003 1222
R: AT, BE, GB, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LI, LU, MC, NL, PT, RO, SE, SI, SK, TR				
CN 1512268	A	20040714	CN 2003-10113198	2003 1226

PRIORITY APPLN. INFO.: JP 2002-382230 A 2002 1227

AB There is provided an IR-sensitive lithog. printing plate capable of direct plate-making based on digital data from a computer or the like, and excellent in development latitude and scratch resistance, which is an IR-sensitive lithog. printing plate comprising a support and a **heat-sensitive** layer, the **heat-sensitive** layer comprising (A) a copolymer having a specific monomer unit having a carboxyl group, (B) an alkali-soluble high mol. weight compound having a sulfonamide group, and (C) a light-heat conversion material.

IT **188601-29-8 604813-16-3 604813-18-5 604813-19-6 604813-23-2**
(IR-sensitive **lithog.** printing plate containing)

RN 188601-29-8 HCAPLUS
CN Benzoic acid, 4-ethenyl-, polymer with ethenylmethylbenzene (9CI) (CA INDEX NAME)

CM 1

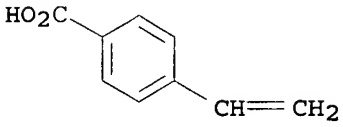
CRN 25013-15-4
CMF C9 H10
CCI IDS

D1— Me

D1— CH═ CH_2

CM 2

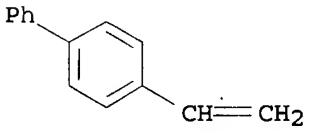
CRN 1075-49-6
CMF C9 H8 O2



RN 604813-16-3 HCAPLUS
CN Benzoic acid, 4-ethenyl-, polymer with 4-ethenyl-1,1'-biphenyl (9CI) (CA INDEX NAME)

CM 1

CRN 2350-89-2
CMF C14 H12



CM 2

CRN 1075-49-6
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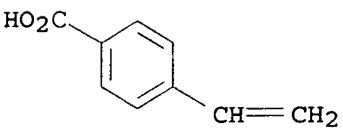
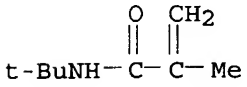


RN 604813-18-5 HCAPLUS

CN Benzoic acid, 4-ethenyl-, polymer with N-(1,1-dimethylethyl)-2-methyl-2-propenamide (9CI) (CA INDEX NAME)

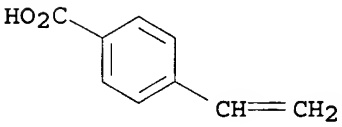
CM 1

CRN 6554-73-0
CMF C8 H15 N O



CM 2

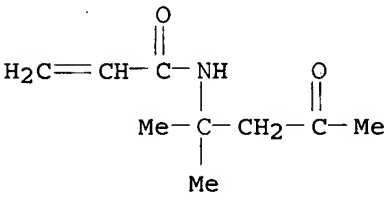
CRN 1075-49-6
CMF C9 H8 O2



RN 604813-19-6 HCAPLUS
CN Benzoic acid, 4-ethenyl-, polymer with N-(1,1-dimethyl-3-oxobutyl)-2-propenamide (9CI) (CA INDEX NAME)

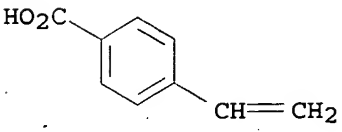
CM 1

CRN 2873-97-4
CMF C9 H15 N O2



CM 2

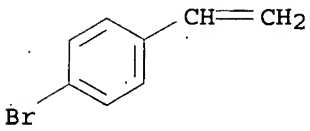
CRN 1075-49-6
CMF C9 H8 O2



RN 604813-23-2 HCAPLUS
CN Benzoic acid, 4-ethenyl-, polymer with 1-bromo-4-ethenylbenzene and N-(1,1-dimethylethyl)-2-propenamide (9CI) (CA INDEX NAME)

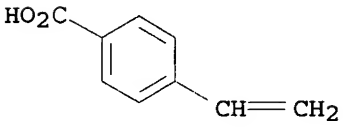
CM 1

CRN 2039-82-9
CMF C8 H7 Br



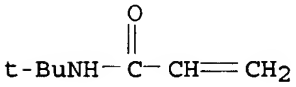
CM 2

CRN 1075-49-6
CMF C9 H8 O2



CM 3

CRN 107-58-4
CMF C7 H13 N O



IC ICM G03F007-039
INCL 430270100; 430286100; 430302000; 101453000
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
IT 146115-88-0 **188601-29-8 604813-16-3**
604813-18-5 604813-19-6 604813-23-2
604813-38-9 604813-40-3 604813-41-4 604813-42-5
604813-43-6 604813-44-7 604813-45-8 604813-46-9
604813-47-0 604813-48-1 604813-50-5 604813-52-7
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604813-59-4 604813-60-7 604813-61-8 604813-62-9
604813-64-1 604813-65-2 604813-66-3 604813-67-4
722484-52-8 722494-08-8 722494-09-9
(IR-sensitive **lithog.** printing plate containing)

L20 ANSWER 13 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:305152 HCAPLUS
DOCUMENT NUMBER: 140:347531
TITLE: Photosensitive lithographic printing plate **precursor**
INVENTOR(S): Kondo, Shunichi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 33 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1407894	A2	20040414	EP 2003-22901	2003 1009
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
JP 2004133125	A2	20040430	JP 2002-296404	2002 1009

PRIORITY APPLN. INFO.: JP 2002-296404 A 2002 1009

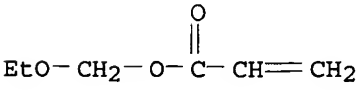
AB A photosensitive lithog. printing plate **precursor** comprises an aluminum support having provided thereon an intermediate layer and a photopolymerizable photosensitive layer in this order, wherein the intermediate layer comprises a copolymer containing a constituting component having an acid group and a constituting component capable of reacting with an alkali developing solution to increase the dissoln. rate in the alkali developing solution The object of the invention is to provide a photosensitive lithog. printing plate which has a high preservation stability and is prevented from the occurrence of background stain by conducting imagewise exposure, development and printing even after the preservation under high temperature and high humidity conditions for a long period of time after the production

IT **679796-25-9**
(photosensitive **lithog.** printing plate **precursor**)

RN 679796-25-9 HCAPLUS
CN Benzoic acid, 4-ethenyl-, polymer with ethoxymethyl 2-propenoate (9CI) (CA INDEX NAME)

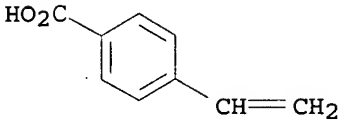
CM 1

CRN 101181-06-0
CMF C6 H10 O3



CM 2

CRN 1075-49-6
CMF C9 H8 O2



IC ICM B41N003-03
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST photosensitive lithog printing plate **precursor**
IT Lithographic plates
(photosensitive lithog. printing plate **precursor**)
IT 3524-68-3 51821-72-8, Isobutyl methacrylate-methacrylic acid-methyl methacrylate copolymer 80937-22-0 90216-38-9, Allyl methacrylate-methacrylic acid copolymer 161255-05-6, Isopropylacrylamide-methacrylic acid-methyl methacrylate copolymer 293329-29-0 461660-75-3 485385-86-2 **679796-25-9**
(photosensitive **lithog.** printing plate **precursor**)

L20 ANSWER 14 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:291555 HCAPLUS
DOCUMENT NUMBER: 140:329560
TITLE: Method of plate-making positive-working lithographic printing plate
INVENTOR(S): Aogo, Toshiaki; Onishi, Hiroaki
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 30 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004109442	A2	20040408	JP 2002-271435	20020918
PRIORITY APPLN. INFO.:			JP 2002-271435	20020918

AB The pos.-working lithog. printing master plate contains an IR absorbing dye and a water-insol. and alkali-soluble resin in a **heat-sensitive** layer on a water-insol. resin- and alkali-soluble resin-based subbing layer formed on the hydrophilic surface of support, in which the solubility of the **heat sensitive** layer in an alkali aqueous solution increases upon receiving an IR irradiation The pos.-working lithog.

printing master plate receives an IR imagewise exposure, and is developed using an alkali developer which contains ≥1 water-soluble polymer compound having sulfonic acid group, carboxylic acid group, phosphonic acid group, and /or salt thereof, a buffer compound, and a base compound

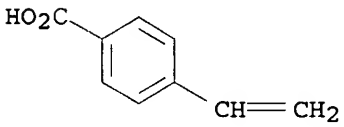
IT **28391-39-1**
(developer for plate-making of pos.-working **lithog.** printing plate)

RN 28391-39-1 HCAPLUS

CN Benzoic acid, 4-ethenyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 1075-49-6
CMF C9 H8 O2



IC ICM G03F007-32
ICS G03F007-00; G03F007-004

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38

IT 25087-26-7, Methacrylic acid homopolymer 25300-64-5, Maleic acid-styrene copolymer 27754-99-0 **28391-39-1** 54640-82-3 83328-59-0
(developer for plate-making of pos.-working **lithog.** printing plate)

L20 ANSWER 15 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:260987 HCAPLUS
DOCUMENT NUMBER: 140:294816
TITLE: Infrared sensitive composition and lithographic printing plate **precursor**
INVENTOR(S): Endo, Akihiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 26 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

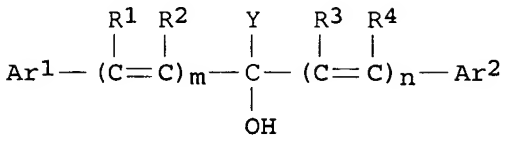
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1403039	A1	20040331	EP 2003-20590	20030918
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
JP 2004125851	A2	20040422	JP 2002-285697	20020

				0930
US 2004063029	A1	20040401	US 2003-673450	2003 0930
CN 1497346	A	20040519	CN 2003-135972	2003 0930

PRIORITY APPLN. INFO.: JP 2002-285697 A 2002 0930

OTHER SOURCE(S): MARPAT 140:294816

GI



I

AB An IR sensitive composition and a lithog. printing plate **precursor** having a large difference in alkali solubility between the exposed portions and unexposed portions (dissoln. discrimination), an excellent latitude in development, and a high sensitivity can be provided when the composition is used for the image-forming layer of a lithog. printing plate **precursor**, which is an IR sensitive composition comprising an alkali-soluble resin having a phenolic hydroxyl group (A), a light-heat converting substance (B) and a leucohydroxy dye (C). The leucohydroxy dye is represented by the general formula I (Ar1, Ar2 = aryl, heteroaryl; R1-R4 = H, alkyl; Y = H, alkyl, aryl, heteroaryl; at least one of Ar1, Ar2 and Y has as a substituent a hydroxy group, an amino group, a monoalkylamino group or a dialkylamino group at the ortho or para position; two of Ar1, Ar2 and Y may link together to from a ring; m, n = 0 or 1).

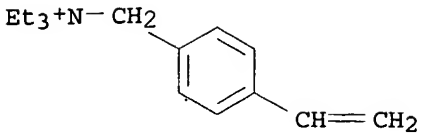
IT **220227-02-1**
(IR sensitive composition and **lithog.** printing plate **precursor**)

RN 220227-02-1 HCAPLUS

CN Benzenemethanaminium, 4-ethenyl-N,N,N-triethyl-, chloride, polymer with 4-ethenylbenzoic acid (9CI) (CA INDEX NAME)

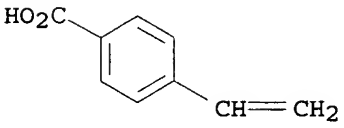
CM 1

CRN 14350-43-7
CMF C15 H24 N . Cl



CM 2

CRN 1075-49-6
CMF C9 H8 O2



IC ICM B41C001-10
ICS G03F007-004; G03C001-73
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST lithog printing plate **precursor** IR sensitive compn
IT Lithographic plates
(IR sensitive composition and lithog. printing plate **precursor**)
IT 467-63-0 510-13-4 603-48-5 6948-88-5 23705-78-4 103250-84-6, m-Cresol-p-cresol-phenol copolymer **220227-02-1** 676259-57-7
(IR sensitive composition and **lithog.** printing plate **precursor**)
REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L20 ANSWER 16 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2003:671500 HCAPLUS
DOCUMENT NUMBER: 139:188366
TITLE: Positive-working **heat sensitive** lithography printing plate with high development latitude
INVENTOR(S): Watanabe, Noriaki
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 26 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE

JP 2003241388	A2	20030827	JP 2002-43565	2002 0220
US 2003183106	A1	20031002	US 2003-364400	2003 0212
US 6849380	B2	20050201		
PRIORITY APPLN. INFO.:			JP 2002-43565 A	2002 0220

AB Title printing plate is obtained by laminating an aluminum substrate, which has been subjected to anode oxidative treatment, an undercoat comprising polymer having acid group-containing components and onium group-containing components, a middle layer comprising a resin which is water-insol. but soluble in alkali, and a **heat-sensitive** layer which comprises a water-insol. but alkali-soluble resin and an IR-absorbing dye and becomes more soluble in aqueous alkali upon heating.

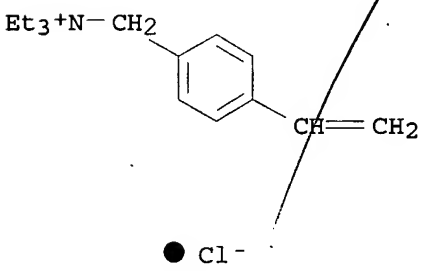
IT **220227-02-1 252721-97-4 252721-98-5**
(undercoat; pos.-working **heat sensitive lithog.** printing plate with high development latitude)

RN 220227-02-1 HCAPLUS

CN Benzenemethanaminium, 4-ethenyl-N,N,N-triethyl-, chloride, polymer with 4-ethenylbenzoic acid (9CI) (CA INDEX NAME)

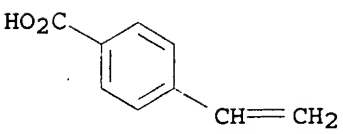
CM 1

CRN 14350-43-7
CMF C15 H24 N . Cl



CM 2

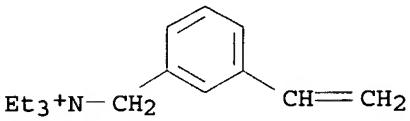
CRN 1075-49-6
CMF C9 H8 O2

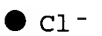


RN 252721-97-4 HCAPLUS
CN Benzenemethanaminium, 3-ethenyl-N,N,N-triethyl-, chloride, polymer with 4-ethenylbenzoic acid and 4-ethenyl-N,N,N-triethylbenzenemethanaminium chloride (9CI) (CA INDEX NAME)

CM 1

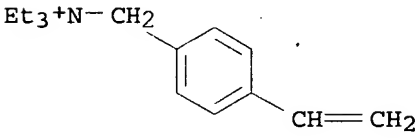
CRN 91277-26-8
CMF C15 H24 N . Cl

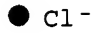




CM 2

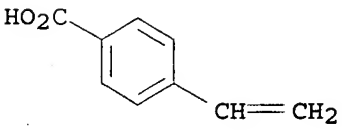
CRN 14350-43-7
CMF C15 H24 N . Cl





CM 3

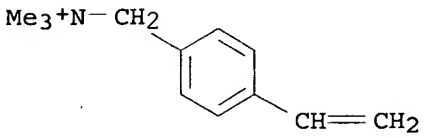
CRN 1075-49-6
CMF C9 H8 O2



RN 252721-98-5 HCAPLUS
CN Benzenemethanaminium, 4-ethenyl-N,N,N-trimethyl-, chloride, polymer with 4-ethenylbenzoic acid (9CI) (CA INDEX NAME)

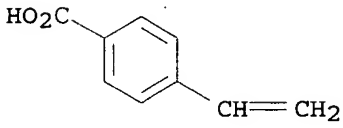
CM 1

CRN 7538-38-7
CMF C12 H18 N . Cl



CM 2

CRN 1075-49-6
CMF C9 H8 O2



IC ICM G03F007-11
ICS B41N001-14; G03F007-00; G03F007-004; G03F007-039
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST pos working **heat sensitive** lithog printing plate
IT Phenolic resins, uses
(novolak, middle layer and **heat-sensitive** layer; pos.-working **heat sensitive** lithog. printing plate with high development latitude)
IT Lithographic plates
(planog.; pos.-working **heat sensitive** lithog. printing plate with high development latitude)
IT 134127-48-3
(IR-absorbing dye; pos.-working **heat sensitive** lithog. printing plate with high development latitude)
IT 7429-90-5, Aluminum, uses
(alloy; pos.-working **heat sensitive** lithog. printing plate with high development latitude)
IT 27029-76-1, m-Cresol-p-cresol-formaldehyde copolymer
(middle layer and **heat-sensitive** layer; pos.-working **heat sensitive** lithog. printing plate with high development latitude)
IT 141634-00-6
(middle layer; pos.-working **heat sensitive** lithog. printing plate with high development latitude)
IT **220227-02-1 252721-97-4 252721-98-5**
(undercoat; pos.-working **heat sensitive**

lithog. printing plate with high development latitude)

L20 ANSWER 17 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2003:299303 HCAPLUS
DOCUMENT NUMBER: 138:329007
TITLE: Presensitized lithography plates for IR laser direct platemaking with suppressed scum
INVENTOR(S): Kawauchi, Ikuo
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 17 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003114519	A2	20030418	JP 2001-309942	2001 1005
PRIORITY APPLN. INFO.:			JP 2001-309942	2001 1005

AB The lithog. plate has a **heat-sensitive** layer containing (A) photothermal converters, (B) aqueous alkali-soluble resins bearing phenolic OH, and (C) waxes which suppress scum on developing, represented by compds. bearing 1-6 groups represented by general formula R1YCOXR2 (X = O, S, NR3; Y = NR3, single bond; R1 = C1-32 alkylene, arylene; R2, R3 = H, C1-18 alkyl, alkenyl, aryl; R1 and/or R2 may bear OH, CO2H, SO3H, sulfinic acid group, PO3H2, phosphonic acid group).

IT **216861-97-1**
(undercoat; presensitized **lithog.** plates with wax-containing **heat-sensitive** layer for IR laser direct platemaking with suppressed scum)

RN 216861-97-1 HCAPLUS
CN Benzenemethanaminium, ar-ethenyl-N,N,N-triethyl-, chloride, polymer with 4-ethenylbenzoic acid (9CI) (CA INDEX NAME)

CM 1

CRN 51241-16-8
CMF C15 H24 N . Cl
CCI IDS

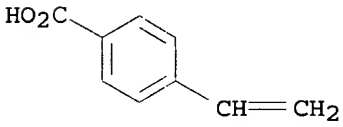
D1— CH═ CH_2

$Et_3{}^+N$— CH_2— D1

● Cl^-

CM 2

CRN 1075-49-6
CMF C9 H8 O2



IC ICM G03F007-00
ICS C09K003-00; G03F007-004
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
ST lithog plate IR laser direct platemaking; wax novolak **heat sensitive** layer lithog; presensitized lithog plate **heat sensitive** layer wax; pos IR laser lithog plate master
IT Polyurethanes, uses
(acrylic, fluorine-containing; presensitized lithog. plates with wax-containing **heat-sensitive** layer for IR laser direct platemaking with suppressed scum)
IT Fluoropolymers, uses
(acrylic-polyurethane-; presensitized lithog. plates with wax-containing **heat-sensitive** layer for IR laser direct platemaking with suppressed scum)
IT Phenolic resins, uses
(novolak, **heat-sensitive** layer binder; presensitized lithog. plates with wax-containing **heat-sensitive** layer for IR laser direct platemaking with suppressed scum)
IT Cyanine dyes
(photothermal converter; presensitized lithog. plates with wax-containing **heat-sensitive** layer for IR laser direct platemaking with suppressed scum)
IT Acrylic polymers, uses

(polyoxyalkylene-, fluorine-containing, graft; presensitized lithog. plates with wax-containing **heat-sensitive** layer for IR laser direct platemaking with suppressed scum)

IT Lithographic plates
(presensitized; presensitized lithog. plates with wax-containing **heat-sensitive** layer for IR laser direct platemaking with suppressed scum)

IT 63-74-1, p-Aminobenzenesulfonamide 79-41-4, Methacrylic acid, reactions
(monomer preparation from; presensitized lithog. plates with wax-containing **heat-sensitive** layer for IR laser direct platemaking with suppressed scum)

IT 56992-87-1P, N-(p-Aminosulfonylphenyl)methacrylamide
(monomer; presensitized lithog. plates with wax-containing **heat-sensitive** layer for IR laser direct platemaking with suppressed scum)

IT 134127-48-3
(photothermal converter; presensitized lithog. plates with wax-containing **heat-sensitive** layer for IR laser direct platemaking with suppressed scum)

IT 124996-93-6P, Acrylonitrile-(p-aminosulfonylphenyl)methacrylamide-ethyl methacrylate copolymer
(presensitized lithog. plates with wax-containing **heat-sensitive** layer for IR laser direct platemaking with suppressed scum)

IT 83563-92-2 92739-54-3 451462-65-0 511531-81-0 511531-82-1
511531-83-2 511531-84-3 511531-85-4 511531-86-5
511531-87-6 511531-88-7 511531-89-8 511531-90-1
511531-91-2 511531-92-3 511531-93-4 511531-94-5
511531-96-7
(presensitized lithog. plates with wax-containing **heat-sensitive** layer for IR laser direct platemaking with suppressed scum)

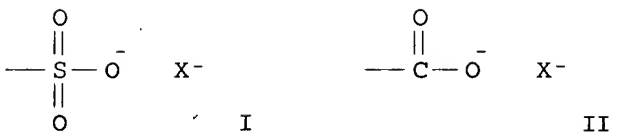
IT **216861-97-1**
(undercoat; presensitized **lithog.** plates with wax-containing **heat-sensitive** layer for IR laser direct platemaking with suppressed scum)

L20 ANSWER 18 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2002:429453 HCAPLUS
DOCUMENT NUMBER: 137:26109
TITLE: Lithographic printing plate **precursor**
INVENTOR(S): Oohashi, Hidekazu; Shimada, Kazuto
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: U.S. Pat. Appl. Publ., 76 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 3
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2002068241	A1	20020606	US 2001-964611	2001 0928
US 6824946	B2	20041130		
JP 2002107929	A2	20020410	JP 2000-303953	2000

				1003
JP 2002144750	A2	20020522	JP 2000-349715	2000 1116
JP 2002174895	A2	20020621	JP 2000-374529	2000 1208
JP 2002174893	A2	20020621	JP 2000-374530	2000 1208
US 2004086799	A1	20040506	US 2003-727633	2003 1205
US 6939658	B2	20050906		
PRIORITY APPLN. INFO.:			JP 2000-303953 A	2000 1003
			JP 2000-349715 A	2000 1116
			JP 2000-374529 A	2000 1208
			JP 2000-374530 A	2000 1208
			US 2001-964611 A3	2001 0928

GI



I II

AB A lithog. printing plate **precursor** comprises a support having a hydrophilic surface having provided thereon an image-forming layer containing a hydrophobic high mol. compound having at least either a functional group represented by the formula I or a functional group represented by the formula II (X+ = iodonium, sulfonium, or diazonium ions). The present invention provides a lithog. printing plate **precursor** which has high sensitivity and causes no stains due to residual films, and is capable of plate-making by scanning exposure with a solid state laser and a semiconductor laser emitting IR rays based on digital signals. The present invention also provides a lithog. printing plate **precursor** which can be developed by water or an aqueous solution, or can be mounted on a printing machine to perform

printing requiring no development.

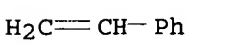
IT **433922-49-7**
(lithog. printing plate precursor)

RN 433922-49-7 HCAPLUS

CN Iodonium, bis[4-(1,1-dimethylpropyl)phenyl]-, salt with 4-ethenylbenzoic acid (1:1), polymer with ethenylbenzene (9CI) (CA INDEX NAME)

CM 1

CRN 100-42-5
CMF C8 H8

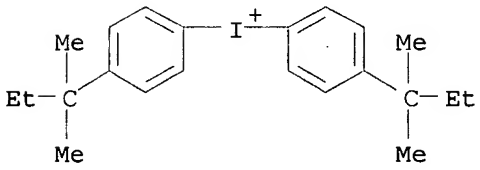


CM 2

CRN 433922-48-6
CMF C22 H30 I . C9 H7 O2

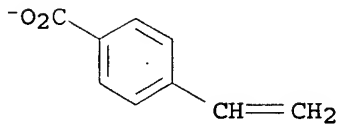
CM 3

CRN 249300-51-4
CMF C22 H30 I



CM 4

CRN 74056-33-0
CMF C9 H7 O2



IC ICM G03F007-021
ICS G03F007-28; G03F007-033; G03F007-038; B41N001-12

INCL 430288100

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38

ST lithog printing plate **precursor** IR laser exposable

IT Lithographic plates
(lithog. printing plate precursor)

IT 134127-48-3 289893-03-4 361542-00-9 427883-12-3
427898-71-3
(IR-absorber dye; lithog. printing plate **precursor**)
IT 496-16-2 52858-60-3 56992-88-2 57758-90-4 150610-19-8
215958-19-3 427883-14-5 427883-16-7 433922-47-5
433922-49-7 433922-51-1 433922-54-4 433922-55-5
433922-56-6
(**lithog.** printing plate **precursor**)
REFERENCE COUNT: 5 THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L20 ANSWER 19 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2002:286047 HCAPLUS
DOCUMENT NUMBER: 136:316957
TITLE: Lithographic printing plate **precursor** having hydrophilic layer and recording layer containing polymer of **heat-sensitive** carboxyl groups
INVENTOR(S): Takahashi, Miki; Yamazaki, Sumiaki
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 25 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

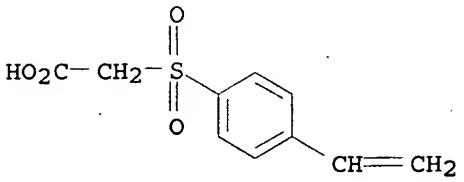
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002113964	A2	20020416	JP 2000-309357	2000 1010

PRIORITY APPLN. INFO.: JP 2000-309357 2000 1010

AB The title lithog. printing plate **precursor** has a hydrophilic layer and a recording layer on a support, wherein the recording layer contains a polymer having a carboxylic acid group or a carboxylate group to be decomposed by heat and wherein the hydrophilic layer is connected to the support by covalent bonds and contains a polymer having hydrophilic groups. The printing plate **precursor** shows the good contact of printing layer with the support, the reduced heat diffusion in the aluminum support to write images with the low energy and provides the printing plate of little soiling and the good printing durability.
IT **265316-27-6 265316-79-8**
(polymer in recording layer of **lithog.** printing plate **precursor**)
RN 265316-27-6 HCAPLUS
CN Acetic acid, [(4-ethenylphenyl)sulfonyl]-, homopolymer (9CI) (CA INDEX NAME)

CM 1

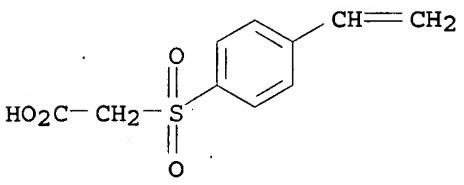
CRN 103945-08-0
CMF C10 H10 O4 S



RN 265316-79-8 HCAPLUS
CN Acetic acid, [(4-ethenylphenyl)sulfonyl]-, sodium salt, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 265316-78-7
CMF C10 H10 O4 S . Na



● Na

IC ICM B41N001-14
ICS G03F007-00; G03F007-004; G03F007-039; G03F007-11
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35
ST lithog printing plate **precursor** hydrophilic layer recording polymer
IT Lithographic plates
(lithog. printing plate **precursor** having hydrophilic layer and recording layer containing polymer of **heat-sensitive** carboxylic groups on support)
IT 9003-01-4DP, Acrylic acid homopolymer, reaction product with 2-(Methacryloyloxy)ethyl isocyanate 30674-80-7DP, 2-(Methacryloyloxy)ethyl isocyanate, reaction product with acrylic polymer 141087-50-5P, Tetraethoxysilane-(3-Methacryloxypropyl)trimethoxysilane copolymer
(hydrophilic layer of lithog. printing plate **precursor**)
IT **265316-27-6** 265316-42-5 **265316-79-8**
265316-94-7 265317-16-6 265317-22-4
(polymer in recording layer of **lithog.** printing plate **precursor**)

L20 ANSWER 20 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2002:265350 HCAPLUS
DOCUMENT NUMBER: 136:316944
TITLE: Lithographic plate **precursors** for

scanning exposure by IR laser
INVENTOR(S): Ohashi, Hidekazu
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 27 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 3
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002107929	A2	20020410	JP 2000-303953	2000 1003
US 2002068241	A1	20020606	US 2001-964611	2001 0928
US 6824946	B2	20041130		
US 2004086799	A1	20040506	US 2003-727633	2003 1205
US 6939658	B2	20050906		

PRIORITY APPLN. INFO.:		
JP 2000-303953	A	2000 1003
JP 2000-349715	A	2000 1116
JP 2000-374529	A	2000 1208
JP 2000-374530	A	2000 1208
US 2001-964611	A3	2001 0928

AB The title lithog. plate has an image-forming layer containing a hydrophobic polymer on a support with a hydrophilic surface, wherein the hydrophobic polymer has functional group -S(=O)2O- X+ and -C(=O)O- X+ (X+ = iodonium, sulfonium, diazonium). The lithog. plate **precursor** shows the high sensitivity and provides printing plates of little soiling caused by residual light-sensitive layers during the plate making.

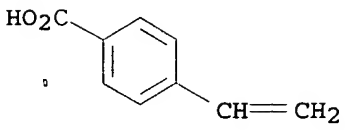
IT **28854-56-0P**
(hydrophobic polymer in **lithog.** plate **precursors**)

RN 28854-56-0 HCAPLUS

CN Benzoic acid, 4-ethenyl-, polymer with ethenylbenzene (9CI) (CA INDEX NAME)

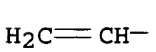
CM 1

CRN 1075-49-6
CMF C9 H8 O2



CM 2

CRN 100-42-5
CMF C8 H8



IC ICM G03F007-038
ICS B41N001-14; G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35
ST lithog plate **precursor** scanning exposure IR laser
IT Light-sensitive materials
Lithographic plates
(lithog. plate **precursors** for scanning exposure by IR laser)
IT 75-03-6, Ethyl iodide 945-51-7, Diphenyl sulfoxide 2049-95-8, tert-Amylbenzene 7758-05-6, Potassium iodate 12027-06-4, Ammonium iodide 16600-92-3, 2-Nitro-1,3,5-benzenetriol
(hydrophobic polymer in lithog. plate **precursors**)
IT 3744-08-9P, Triphenylsulfonium iodide 215253-66-0P, Benzenediazonium,2,4,6-triethoxy- 220476-27-7P, 2-Nitro-1,3,5-triethoxybenzene 220476-28-8P, 2,4,6-Triethoxyaniline hydrochloride 365971-60-4P, Iodonium,bis[4-(1,1-dimethylpropyl)phenyl]-,iodide
(hydrophobic polymer in lithog. plate **precursors**)
IT 25085-34-1P 27234-22-6P **28854-56-0P** 259263-07-5DP, Styrene-Cyclohexyl p-styrenesulfonate copolymer, hydrolyzed, salt with iodonium, sulfonium, or diazonium 264871-12-7P 409350-26-1P
(hydrophobic polymer in **lithog.** plate **precursors**)

L20 ANSWER 21 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2002:219919 HCAPLUS
DOCUMENT NUMBER: 136:239137
TITLE: Thermal positive-type lithographic plate using anodized aluminum support
INVENTOR(S): Endo, Tadashi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 36 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002082443	A2	20020322	JP 2000-272895	2000 0908
PRIORITY APPLN. INFO.:			JP 2000-272895	2000 0908

AB In the material comprising a coarsened and anodized Al support coated with a photosensitive layer whose solubility to an alkaline developer changes by heating, the anodized film has micropores with average size ≤20 nm and d. ≥300 number/μm2. The material shows high sensitivity.

IT **214279-68-2P**, p-Vinylbenzoic acid-vinylbenzyltrimethylammonium chloride copolymer **220227-02-1P**, Triethyl(p-vinylbenzyl)ammonium chloride-p-vinylbenzoic acid copolymer **252721-97-4P**, Triethyl(m-vinylbenzyl)ammonium chloride-triethyl(p-vinylbenzyl)ammonium chloride-p-vinylbenzoic acid copolymer
(intermediate layer; **heat-sensitive lithog.** plate using anodized aluminum support with size-controlled micropores)

RN 214279-68-2 HCAPLUS

CN Benzenemethanaminium, ar-ethenyl-N,N,N-trimethyl-, chloride, polymer with 4-ethenylbenzoic acid (9CI) (CA INDEX NAME)

CM 1

CRN 26616-35-3
CMF C12 H18 N . Cl
CCI IDS

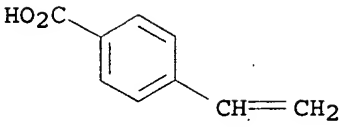
D1— CH═ CH_2

$Me_3{}^+N$— CH_2— D1

● Cl^-

CM 2

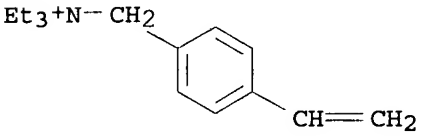
CRN 1075-49-6
CMF C9 H8 O2



RN 220227-02-1 HCAPLUS
CN Benzenemethanaminium, 4-ethenyl-N,N,N-triethyl-, chloride, polymer with 4-ethenylbenzoic acid (9CI) (CA INDEX NAME)

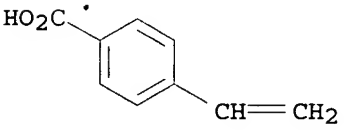
CM 1

CRN 14350-43-7
CMF C15 H24 N . Cl



CM 2

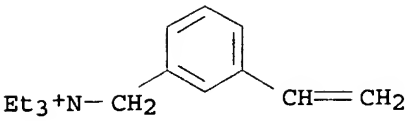
CRN 1075-49-6
CMF C9 H8 O2



RN 252721-97-4 HCAPLUS
CN Benzenemethanaminium, 3-ethenyl-N,N,N-triethyl-, chloride, polymer with 4-ethenylbenzoic acid and 4-ethenyl-N,N,N-triethylbenzenemethanaminium chloride (9CI) (CA INDEX NAME)

CM 1

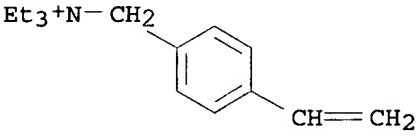
CRN 91277-26-8
CMF C15 H24 N . Cl



● Cl⁻

CM 2

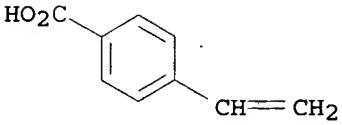
CRN 14350-43-7
CMF C15 H24 N . Cl



● Cl⁻

CM 3

CRN 1075-49-6
CMF C9 H8 O2



IC ICM G03F007-09
ICS B41N001-08; B41N001-14; B41N003-03; C25D011-04; C25D011-16; G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT Anodization
Lithographic plates
(**heat-sensitive** lithog. plate using anodized aluminum support with size-controlled micropores)
IT Phenolic resins, uses
(**heat-sensitive** lithog. plate using anodized aluminum support with size-controlled micropores)
IT 62200-40-2
(**heat-sensitive** lithog. plate using anodized aluminum support with size-controlled micropores)

IT **214279-68-2P**, p-Vinylbenzoic acid-vinylbenzyltrimethylammonium chloride copolymer **220227-02-1P**, Triethyl(p-vinylbenzyl)ammonium chloride-p-vinylbenzoic acid copolymer **252721-97-4P**, Triethyl(m-vinylbenzyl)ammonium chloride-triethyl(p-vinylbenzyl)ammonium chloride-p-vinylbenzoic acid copolymer
(intermediate layer; **heat-sensitive** **lithog.** plate using anodized aluminum support with size-controlled micropores)

IT 124996-93-6P, Acrylonitrile-N-(p-aminosulfonylphenyl)methacrylamide-ethyl methacrylate copolymer
(photosensitive layer; **heat-sensitive** lithog. plate using anodized aluminum support with size-controlled micropores)

IT 27029-76-1, m-Cresol-p-cresol-formaldehyde copolymer
(photosensitive layer; **heat-sensitive** lithog. plate using anodized aluminum support with size-controlled micropores)

L20 ANSWER 22 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2002:61464 HCAPLUS
DOCUMENT NUMBER: 136:126583
TITLE: Lithographic printing original plates with high printability
INVENTOR(S): Taninaka, Hiromitsu; Yamazaki, Sumiaki
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 26 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002019317	A2	20020123	JP 2000-206906	2000 0707

PRIORITY APPLN. INFO.: JP 2000-206906 2000 0707

OTHER SOURCE(S): MARPAT 136:126583
AB In the original plates having **heat-sensitive** layers containing ≥1 components selected from thermoplastic polymer fine particles, thermosetting polymer fine particles, polymer fine particles having heat-reactive functional groups, and microcapsules containing hydrophilic compds. on hydrophilic supports, the **heat-sensitive** layers contain hydrophilic polymers which become hydrophobic by heat. Water-soluble overcoat layers may contain the hydrophilic polymers. The original plates are suitable for scanning exposure based on digital signals and show good on-press developability.

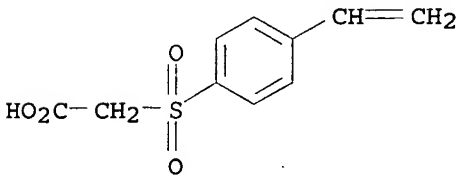
IT **265316-79-8 265316-83-4 265316-84-5 265316-86-7 390801-06-6**
(on-press developable **lithog.** original plates having **heat-sensitive** hydrophilic polymer layers)

RN 265316-79-8 HCAPLUS
CN Acetic acid, [(4-ethenylphenyl)sulfonyl]-, sodium salt,

homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 265316-78-7
CMF C10 H10 O4 S . Na

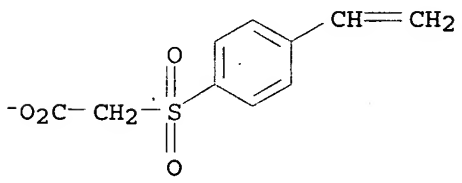


● Na

RN 265316-83-4 HCAPLUS
CN Methanaminium, N,N,N-trimethyl-, salt with [(4-ethenylphenyl)sulfonyl]acetic acid (1:1), homopolymer (9CI) (CA INDEX NAME)

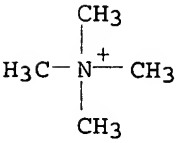
CM 1

CRN 265316-82-3
CMF C10 H9 O4 S



CM 2

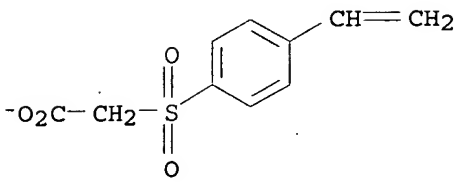
CRN 51-92-3
CMF C4 H12 N



RN 265316-84-5 HCAPLUS
CN 1-Butanaminium, N,N,N-tributyl-, salt with [(4-ethenylphenyl)sulfonyl]acetic acid (1:1), homopolymer (9CI) (CA INDEX NAME)

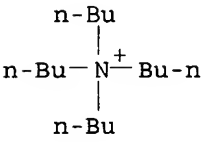
CM 1

CRN 265316-82-3
CMF C10 H9 O4 S



CM 2

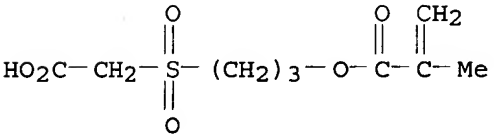
CRN 10549-76-5
CMF C16 H36 N



RN 265316-86-7 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 3-[(carboxymethyl)sulfonyl]propyl ester, sodium salt, homopolymer (9CI) (CA INDEX NAME)

CM 1

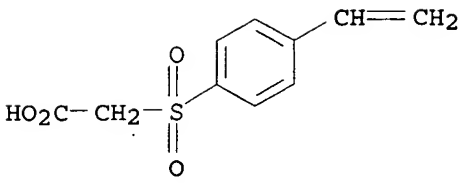
CRN 265316-85-6
CMF C9 H14 O6 S . Na



RN 390801-06-6 HCAPLUS
CN 2-Propenoic acid, 2-hydroxyethyl ester, polymer with sodium [(4-ethenylphenyl)sulfonyl]acetate (9CI) (CA INDEX NAME)

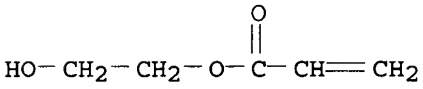
CM 1

CRN 265316-78-7
CMF C10 H10 O4 S . Na



CM 2

CRN 818-61-1
CMF C5 H8 O3



IC ICM B41N001-14
ICS G03F007-00; G03F007-004; G03F007-039; G03F007-11
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST lithog original plate **heat sensitive** hydrophilic polymer; printability lithog original plate hydrophilic polymer; developability onpress lithog original plate hydrophilic polymer
IT Polyesters, preparation
(fine particles; on-press developable lithog. original plates having **heat-sensitive** hydrophilic polymer layers)
IT Lithographic plates
(on-press developable lithog. original plates having **heat-sensitive** hydrophilic polymer layers)
IT 390801-07-7P 390801-08-8P, Takenate D 110N-Epikote 1004-PVA 217EE copolymer 390801-09-9P, Epikote 1004-PVA 217EE-trimethylolpropane-xylylene diisocyanate adduct copolymer
(fine particles; on-press developable lithog. original plates having **heat-sensitive** hydrophilic polymer layers)
IT 9003-53-6, Polystyrene
(fine particles; on-press developable lithog. original plates having **heat-sensitive** hydrophilic polymer layers)
IT **265316-79-8 265316-83-4 265316-84-5 265316-86-7** 265316-90-3 265316-98-1 **390801-06-6**
(on-press developable **lithog.** original plates having **heat-sensitive** hydrophilic polymer layers)
IT 37321-70-3, JIS A 1050
(supports; on-press developable lithog. original plates having **heat-sensitive** hydrophilic polymer layers)

L20 ANSWER 23 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2002:35841 HCAPLUS
DOCUMENT NUMBER: 136:103176
TITLE: Photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compositions useful for lithographic patterning containing them
INVENTOR(S): Kaneda, Takayuki; Kimura, Masashi; Kanaya, Ryuichiro
PATENT ASSIGNEE(S): Asahi Chemical Industry Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 21 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002012665	A2	20020115	JP 2000-335097	2000 1101
PRIORITY APPLN. INFO.:			JP 2000-130480 A	2000 0428

AB The resins are obtained from the reaction products of a polyamide bearing OH groups partially with OCN(CH2)mOCOC(R1):CR2R3 (R1-3 = H, C1-3 aliphatic groups; m = 2-10), and used in compns. containing photoinitiators, crosslinkers and diluents for neg.-working photoresists in patterning of semiconductor devices. Thus, condensing 2,2-bis(3-amino-4-hydroxyphenyl)hexafluoropropane with 4,4'-diphenyl ether dicarboxylic acid dichloride, end-blocking the resulting polyamide with phthalic anhydride, purifying, and reacting the blocked product with 2-isocyanatoethyl methacrylate (at an amount equivalent to 40 mol% of OH groups on the product) gave a polybenzoxazole **precursor** 100 parts of which was combined with tetraethylene glycol dimethacrylate 40, 1-phenyl-propanedione-2-(o-benzoyl) oxime 6, Michler's ketone 2, 3-aminopropyltrimethoxysilane 6, N-nitrosodiphenylamine 0.1 and N-methyl-2-pyrrolidone 230 parts to give a neg.-working photoresist with good light curability and developing property by alkali.

IT **389104-92-1DP**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer 2-isocyanatoethyl methacrylate ester-tetraethylene glycol dimethacrylate copolymer, reaction products with termination acids **389104-92-1P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer 2-isocyanatoethyl methacrylate ester-tetraethylene glycol dimethacrylate copolymer **389104-93-2DP**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer 2-isocyanatoethyl methacrylate ester-N,N'-di(2-methacryloxyethyl)urea copolymer, reaction products with termination acids **389104-94-3P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer 2-isocyanatoethyl methacrylate ester-N,N'-di(2-methacryloxyethyl)urea-tetraethylene

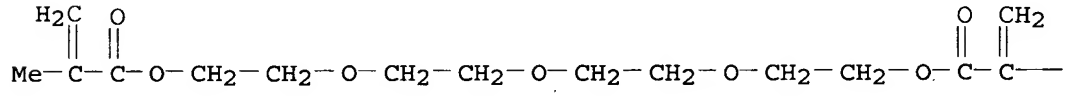
glycol dimethacrylate copolymer
(photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for **lithog.** patterning containing them)

RN 389104-92-1 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, oxybis(2,1-ethanediyloxy-2,1-ethanediyl) ester, polymer with 4,4'-oxybis[benzoyl chloride] polymer with 4,4'-[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene]bis[2-aminophenol] [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (9CI) (CA INDEX NAME)

CM 1

CRN 109-17-1
CMF C16 H26 O7

PAGE 1-A



PAGE 1-B

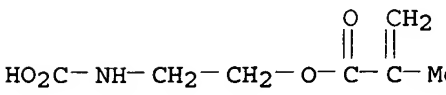
— Me

CM 2

CRN 389104-91-0
CMF (C15 H12 F6 N2 O2 . C14 H8 Cl2 O3)x . x C7 H11 N O4

CM 3

CRN 96571-20-9
CMF C7 H11 N O4

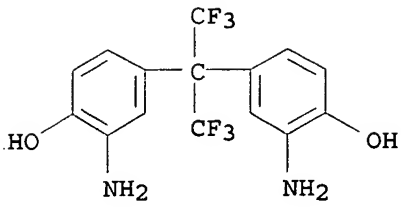


CM 4

CRN 133440-72-9
CMF (C15 H12 F6 N2 O2 . C14 H8 Cl2 O3)x
CCI PMS

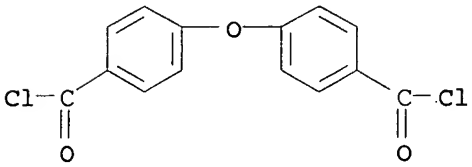
CM 5

CRN 83558-87-6
CMF C15 H12 F6 N2 O2



CM 6

CRN 7158-32-9
CMF C14 H8 Cl2 O3

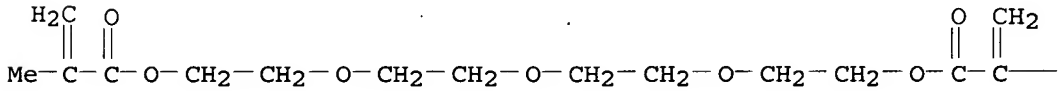


RN 389104-92-1 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, oxybis(2,1-ethanediyloxy-2,1-ethanediyl) ester, polymer with 4,4'-oxybis[benzoyl chloride] polymer with 4,4'-[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene]bis[2-aminophenol] [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (9CI) (CA INDEX NAME)

CM 1

CRN 109-17-1
CMF C16 H26 O7

PAGE 1-A



PAGE 1-B

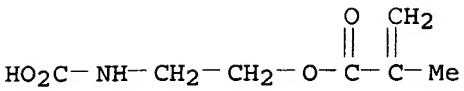
— Me

CM 2

CRN 389104-91-0
CMF (C15 H12 F6 N2 O2 . C14 H8 Cl2 O3)x . x C7 H11 N O4

CM 3

CRN 96571-20-9
CMF C7 H11 N O4

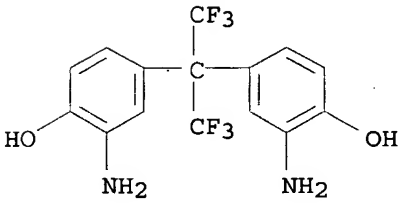


CM 4

CRN 133440-72-9
CMF (C15 H12 F6 N2 O2 . C14 H8 Cl2 O3)x
CCI PMS

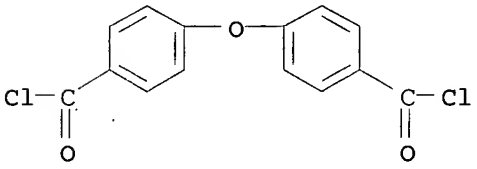
CM 5

CRN 83558-87-6
CMF C15 H12 F6 N2 O2



CM 6

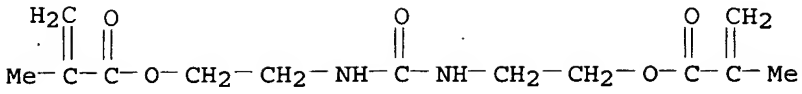
CRN 7158-32-9
CMF C14 H8 Cl2 O3



RN 389104-93-2 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, carbonylbis(imino-2,1-ethanediyl) ester, polymer with 4,4'-oxybis[benzoyl chloride] polymer with 4,4'-[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene]bis[2-aminophenol] [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (9CI) (CA INDEX NAME)

CM 1

CRN 86219-64-9
CMF C13 H20 N2 O5

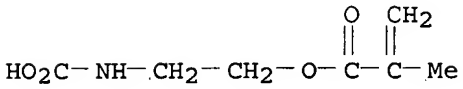


CM 2

CRN 389104-91-0
CMF (C15 H12 F6 N2 O2 . C14 H8 Cl2 O3)x . x C7 H11 N O4

CM 3

CRN 96571-20-9
CMF C7 H11 N O4

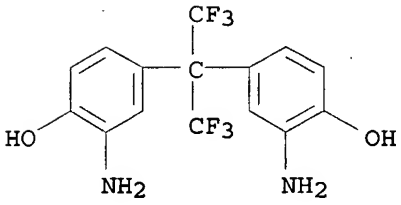


CM 4

CRN 133440-72-9
CMF (C15 H12 F6 N2 O2 . C14 H8 Cl2 O3)x
CCI PMS

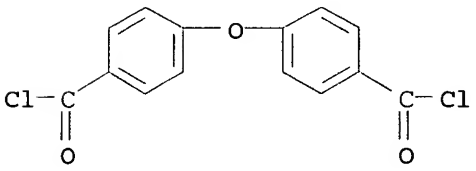
CM 5

CRN 83558-87-6
CMF C15 H12 F6 N2 O2



CM 6

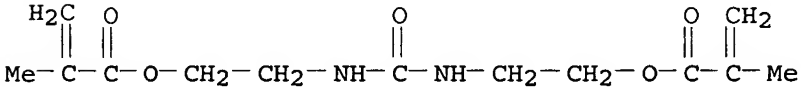
CRN 7158-32-9
CMF C14 H8 Cl2 O3



RN 389104-94-3 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, carbonylbis(imino-2,1-ethanediyl) ester, polymer with 4,4'-oxybis[benzoyl chloride] polymer with 4,4'-[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene]bis[2-aminophenol] [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate, and oxybis(2,1-ethanediyloxy-2,1-ethanediyl) bis(2-methyl-2-propenoate) (9CI) (CA INDEX NAME)

CM 1

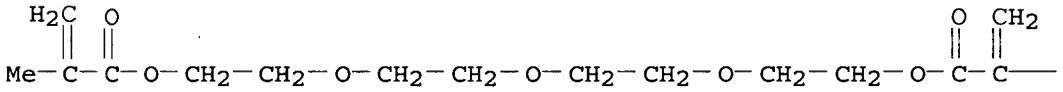
CRN 86219-64-9
CMF C13 H20 N2 O5



CM 2

CRN 109-17-1
CMF C16 H26 O7

PAGE 1-A



PAGE 1-B

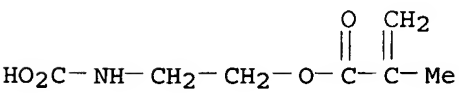
— Me

CM 3

CRN 389104-91-0
CMF (C15 H12 F6 N2 O2 . C14 H8 Cl2 O3)x . x C7 H11 N O4

CM 4

CRN 96571-20-9
CMF C7 H11 N O4

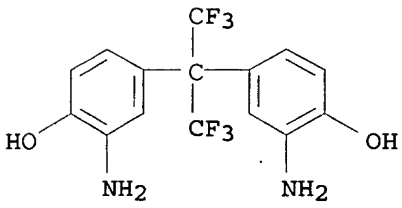


CM 5

CRN 133440-72-9
CMF (C15 H12 F6 N2 O2 . C14 H8 Cl2 O3)x
CCI PMS

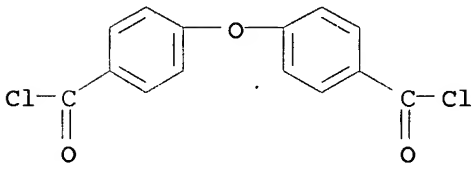
CM 6

CRN 83558-87-6
CMF C15 H12 F6 N2 O2



CM 7

CRN 7158-32-9
CMF C14 H8 Cl2 O3



IT **389104-83-0P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, phthalic anhydride-terminated, ester with 2-isocyanatoethyl methacrylate **389104-84-1P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, terminated with methanesulfonyl chloride, carbamate ester with 2-isocyanatoethyl methacrylate **389104-85-2P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, terminated with p-toluenesulfonyl chloride, carbamate ester with 2-isocyanatoethyl methacrylate **389104-86-3P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, terminated with 5-norbornene-2,3-dicarboxylic anhydride, carbamate ester with 2-isocyanatoethyl methacrylate **389104-87-4P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, terminated with glutaric anhydride, carbamate ester with 2-isocyanatoethyl methacrylate **389104-89-6P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, terminated with di-tert-butyl carbonate, carbamate ester with 2-isocyanatoethyl methacrylate **389104-90-9P**,

2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, carbamate ester with 2-isocyanatoethyl methacrylate **389104-95-4P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, terminated with cyclohexane-1,2-dicarboxylic anhydride, carbamate ester with 2-isocyanatoethyl methacrylate
(photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for **lithog.** patterning containing them)

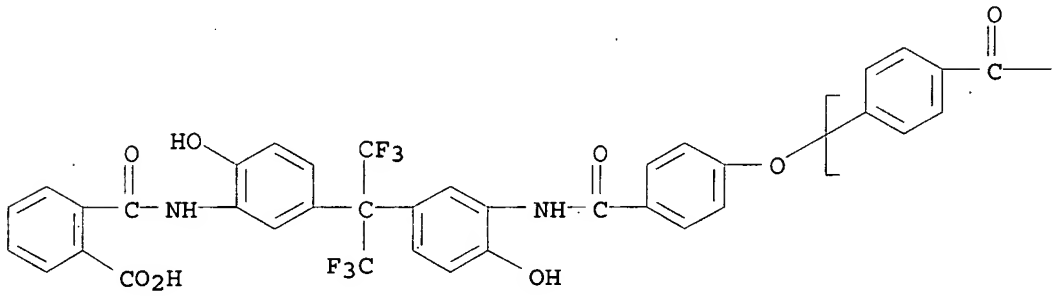
RN 389104-83-0 HCAPLUS

CN Poly[oxy-1,4-phenylenecarbonylimino(6-hydroxy-1,3-phenylene)[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene](4-hydroxy-1,3-phenylene)iminocarbonyl-1,4-phenylene], α-[4-[[[3-[1-[3-[(2-carboxybenzoyl)amino]-4-hydroxyphenyl]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]-6-hydroxyphenyl]amino]carbonyl]phenyl]-ω-[4-[[[3-[1-[3-[(2-carboxybenzoyl)amino]-4-hydroxyphenyl]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]-6-hydroxyphenyl]amino]carbonyl]phenoxy]-, [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (9CI) (CA INDEX NAME)

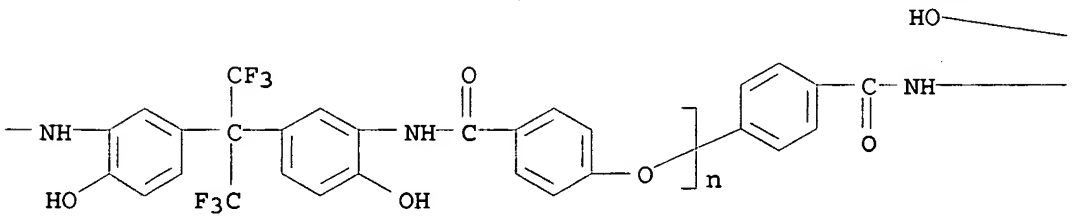
CM 1

CRN 389077-92-3
CMF (C29 H18 F6 N2 O5)n C60 H38 F12 N4 O13
CCI PMS

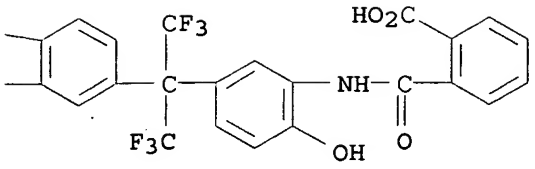
PAGE 1-A



PAGE 1-B

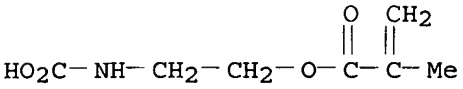


PAGE 1-C



CM 2

CRN 96571-20-9
CMF C7 H11 N O4

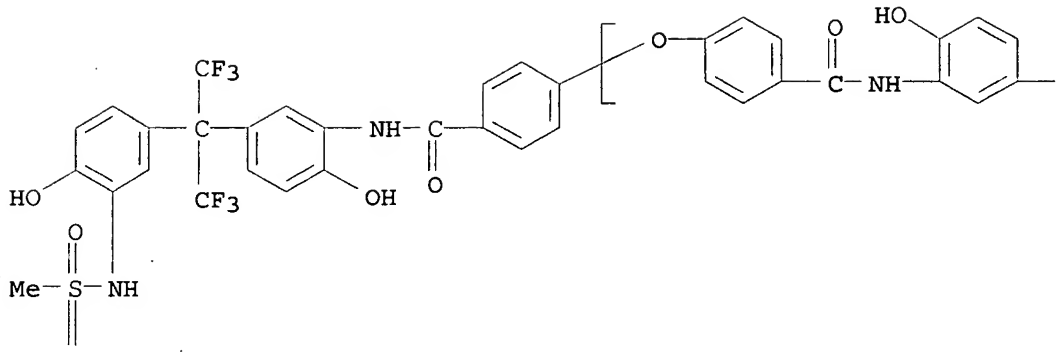


RN 389104-84-1 HCAPLUS
CN Poly[oxy-1,4-phenylenecarbonylimino(6-hydroxy-1,3-phenylene)[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene](4-hydroxy-1,3-phenylene)iminocarbonyl-1,4-phenylene], α-[4-[[[6-hydroxy-3-[2,2,2-trifluoro-1-[4-hydroxy-3-[(methylsulfonyl)amino]phenyl]-1-(trifluoromethyl)ethyl]phenyl]amino]carbonyl]phenyl]-ω-[4-[[[6-hydroxy-3-[2,2,2-trifluoro-1-[4-hydroxy-3-[(methylsulfonyl)amino]phenyl]-1-(trifluoromethyl)ethyl]phenyl]amino]carbonyl]phenoxy]-, [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (9CI) (CA INDEX NAME)

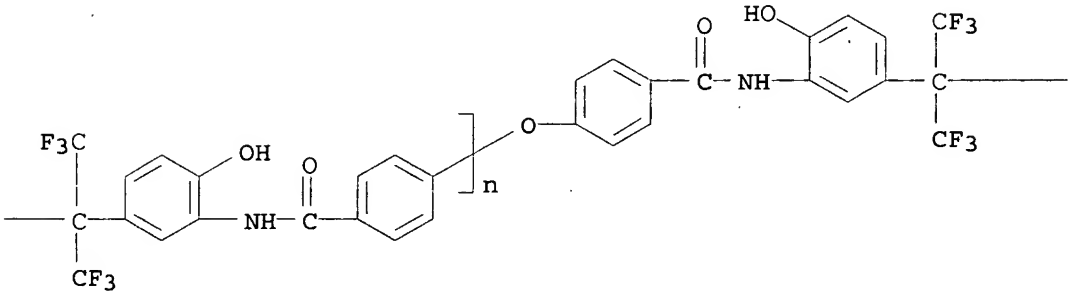
CM 1

CRN 389077-94-5
CMF (C29 H18 F6 N2 O5)n C46 H34 F12 N4 O11 S2
CCI PMS

PAGE 1-A



PAGE 1-B



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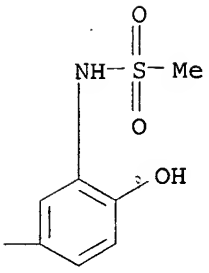
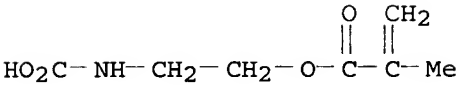


PAGE 2-A

CM 2

CRN 96571-20-9
CMF C7 H11 N O4

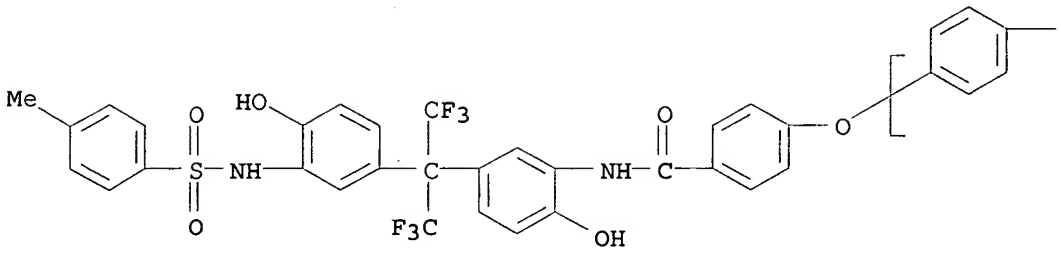


RN 389104-85-2 HCAPLUS
CN Poly[oxy-1,4-phenylenecarbonylimino(6-hydroxy-1,3-phenylene)[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene](4-hydroxy-1,3-phenylene)iminocarbonyl-1,4-phenylene], α-[4-[[[6-hydroxy-3-[2,2,2-trifluoro-1-[4-hydroxy-3-[[(4-methylphenyl)sulfonyl]amino]phenyl]-1-(trifluoromethyl)ethyl]phenyl]amino]carbonyl]phenyl]-ω-[4-[[[6-hydroxy-3-[2,2,2-trifluoro-1-[4-hydroxy-3-[[(4-methylphenyl)sulfonyl]amino]phenyl]-1-(trifluoromethyl)ethyl]phenyl]amino]carbonyl]phenoxy]-, [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (9CI) (CA INDEX NAME)

CM 1

CRN 389077-95-6
CMF (C29 H18 F6 N2 O5)n C58 H42 F12 N4 O11 S2
CCI PMS

PAGE 1-A



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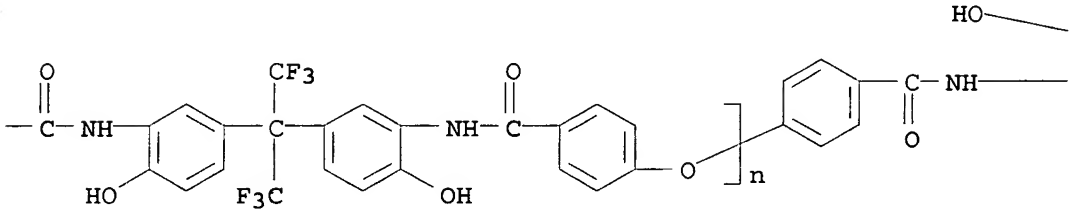

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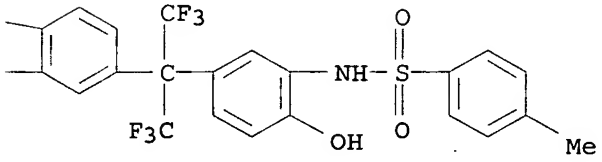
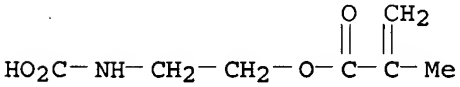


CM 2

CRN 96571-20-9
CMF C7 H11 N O4



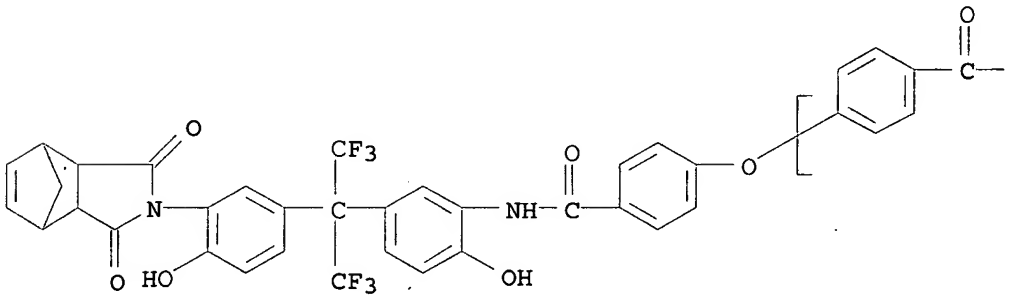
RN 389104-86-3 HCAPLUS
CN Poly[oxy-1,4-phenylenecarbonylimino(6-hydroxy-1,3-phenylene)[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene](4-hydroxy-1,3-phenylene)iminocarbonyl-1,4-phenylene], α-[4-[[[3-[2,2,2-trifluoro-1-[3-(1,3,3a,4,7,7a-hexahydro-1,3-dioxo-4,7-methano-2H-isoindol-2-yl)-4-hydroxyphenyl]-1-(trifluoromethyl)ethyl]-6-

hydroxyphenyl]amino]carbonyl]phenyl]-ω-[4-[[[3-[2,2,2-trifluoro-1-[3-(1,3,3a,4,7,7a-hexahydro-1,3-dioxo-4,7-methano-2H-isoindol-2-yl)-4-hydroxyphenyl]-1-(trifluoromethyl)ethyl]-6-hydroxyphenyl]amino]carbonyl]phenoxy]-, [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (9CI) (CA INDEX NAME)

CM 1

CRN 389077-97-8
CMF (C29 H18 F6 N2 O5)n C62 H42 F12 N4 O11
CCI PMS

PAGE 1-A



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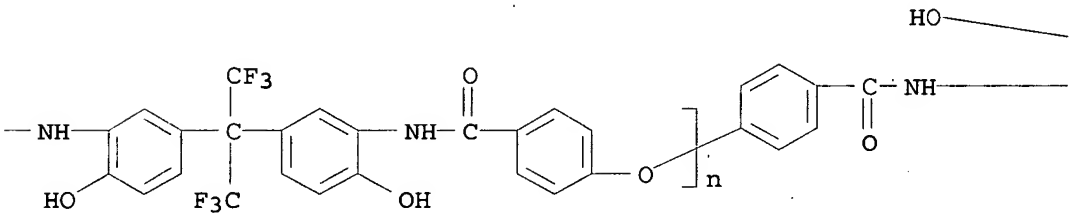
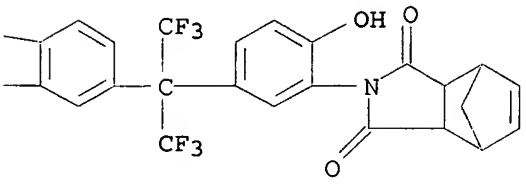
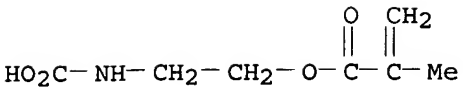


PAGE 1-C



CM 2

CRN 96571-20-9
CMF C7 H11 N O4

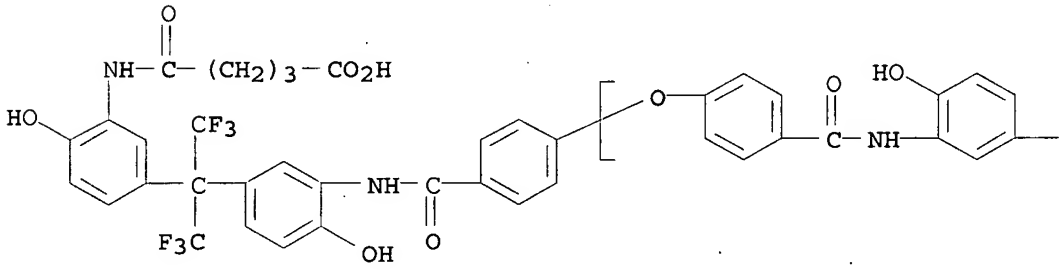


RN 389104-87-4 HCAPLUS
CN Poly[oxy-1,4-phenylenecarbonylimino(6-hydroxy-1,3-phenylene)[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene](4-hydroxy-1,3-phenylene)iminocarbonyl-1,4-phenylene], α-[4-[[[3-[1-[3-[(4-carboxy-1-oxobutyl)amino]-4-hydroxyphenyl]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]-6-hydroxyphenyl]amino]carbonyl]phenyl]-ω-[4-[[[3-[1-[3-[(4-carboxy-1-oxobutyl)amino]-4-hydroxyphenyl]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]-6-hydroxyphenyl]amino]carbonyl]phenoxy]- (9CI) (CA INDEX NAME)

CM 1

CRN 389077-99-0
CMF (C29 H18 F6 N2 O5)n C54 H42 F12 N4 O13
CCI PMS

PAGE 1-A



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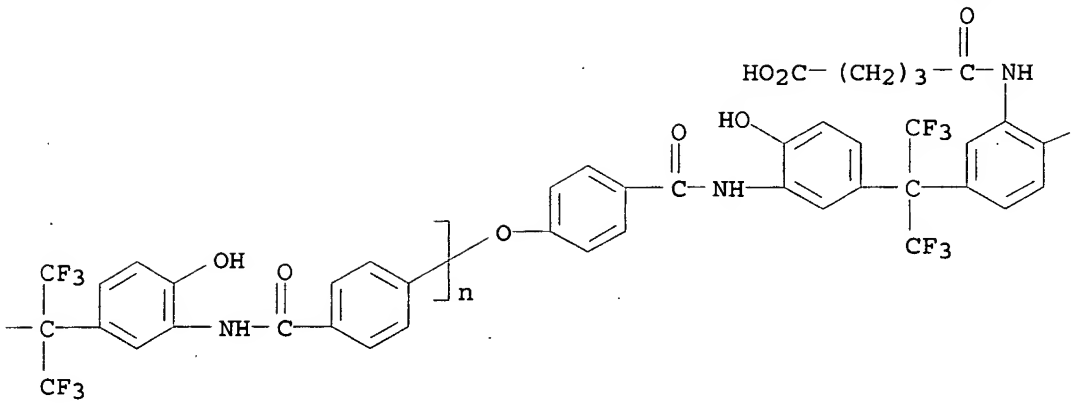
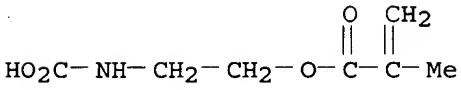


PAGE 1-C

CM 2

CRN 96571-20-9
CMF C7 H11 N O4

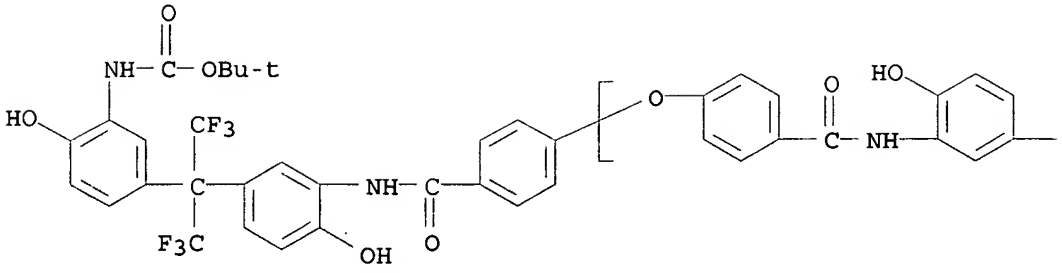


RN 389104-89-6 HCAPLUS
CN Poly[oxy-1,4-phenylenecarbonylimino(6-hydroxy-1,3-phenylene)[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene](4-hydroxy-1,3-phenylene)iminocarbonyl-1,4-phenylene], α-[4-[[[3-[1-[3-[[(1,1-dimethylethoxy)carbonyl]amino]-4-hydroxyphenyl]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]-6-hydroxyphenyl]amino]carbonyl]phenyl]-ω-[4-[[[3-[1-[3-[[(1,1-dimethylethoxy)carbonyl]amino]-4-hydroxyphenyl]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]-6-hydroxyphenyl]amino]carbonyl]phenoxy]-, [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (9CI) (CA INDEX NAME)

CM 1

CRN 389104-88-5
CMF (C29 H18 F6 N2 O5)n C54 H46 F12 N4 O11
CCI PMS

PAGE 1-A



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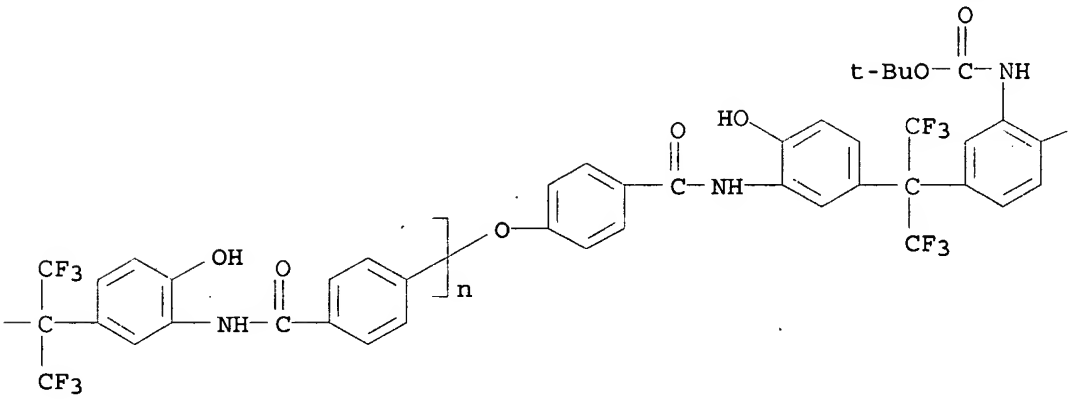

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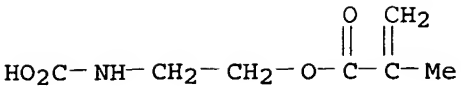
CM 2 .

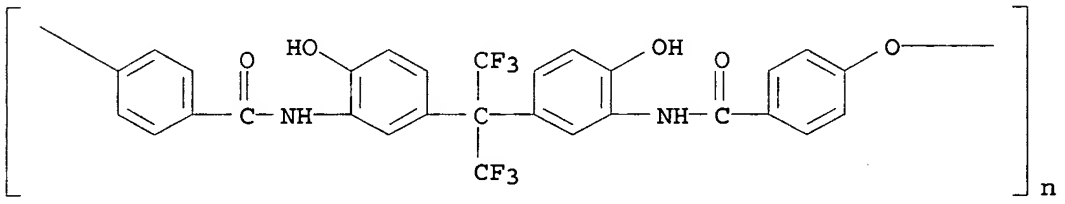
CRN 96571-20-9
CMF C7 H11 N O4



RN 389104-90-9 HCAPLUS
CN Poly[oxy-1,4-phenylenecarbonylimino(6-hydroxy-1,3-phenylene)[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene](4-hydroxy-1,3-phenylene)iminocarbonyl-1,4-phenylene], [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (ester) (9CI) (CA INDEX NAME)

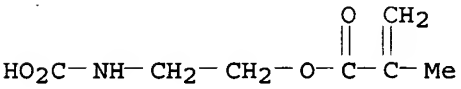
CM 1

CRN 112480-82-7
CMF (C29 H18 F6 N2 O5)n
CCI PMS



CM 2

CRN 96571-20-9
CMF C7 H11 N O4

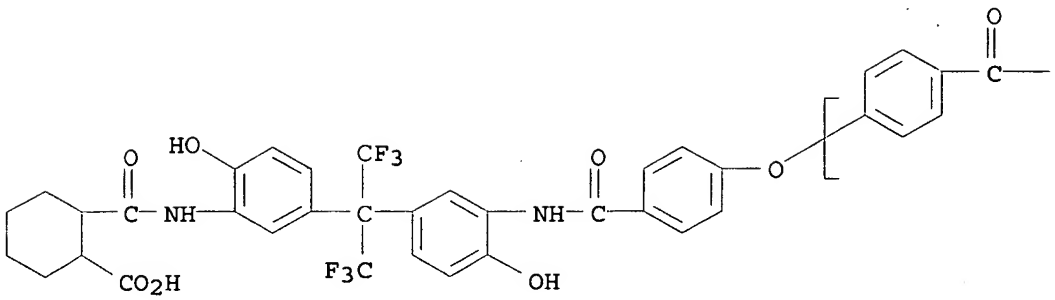


RN 389104-95-4 HCAPLUS
CN Poly[oxy-1,4-phenylenecarbonylimino(6-hydroxy-1,3-phenylene)[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene](4-hydroxy-1,3-phenylene)iminocarbonyl-1,4-phenylene], α-[4-[[[3-[1-[3-[[(2-carboxycyclohexyl)carbonyl]amino]-4-hydroxyphenyl]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]-6-hydroxyphenyl]amino]carbonyl]phenyl]-ω-[4-[[[3-[1-[3-[[(2-carboxycyclohexyl)carbonyl]amino]-4-hydroxyphenyl]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]-6-hydroxyphenyl]amino]carbonyl]phenoxy]-, [2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]carbamate (9CI) (CA INDEX NAME)

CM 1

CRN 389078-02-8
CMF (C29 H18 F6 N2 O5)n C60 H50 F12 N4 O13
CCI PMS

PAGE 1-A



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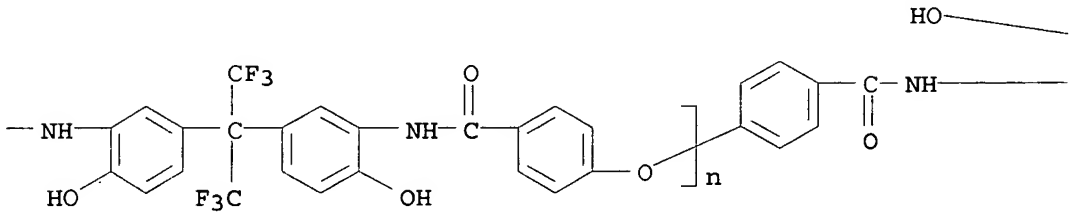

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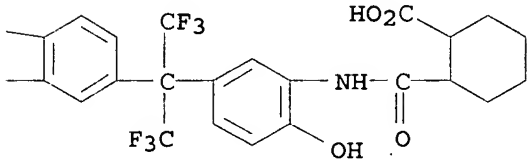
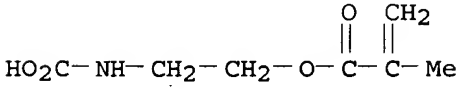


CM 2

CRN 96571-20-9
CMF C7 H11 N O4



IC ICM C08G073-22
ICS C08K005-00; C08L079-06; G03F007-038; G03F007-40; H01L021-027
CC 37-3 (Plastics Manufacture and Processing)
Section cross-reference(s): 74, 76
ST neg working photoresist hydroxy polyamide isocyanatoethyl methacrylate modified resin; semiconductor device lithog patterning acrylic hydroxy polyamide polybenzoxazole

precursor

IT Polyethers, preparation
(acrylic-polyamide-, fluorine-containing; photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for lithog. patterning containing them)

IT Fluoropolymers, preparation
(acrylic-polyamide-polyether-; photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for lithog. patterning containing them)

IT Polyethers, preparation
(acrylic-polybenzoxazole-, fluorine-containing; photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for lithog. patterning containing them)

IT Fluoropolymers, preparation
(acrylic-polybenzoxazole-polyether-; photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for lithog. patterning containing them)

IT Polybenzoxazoles
(acrylic-polyether-, fluorine-containing; photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for lithog. patterning containing them)

IT Polyamides, preparation
(acrylic-polyether-, fluorine-containing; photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for lithog. patterning containing them)

IT Dielectric films
Photoresists
Semiconductor device fabrication
(photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for lithog. patterning containing them)

IT Acrylic polymers, preparation
(polybenzoxazole-polyether-, fluorine-containing; photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for lithog. patterning containing them)

IT **389104-92-1DP**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer 2-isocyanatoethyl methacrylate ester-tetraethylene glycol dimethacrylate copolymer, reaction products with termination acids **389104-92-1P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer 2-isocyanatoethyl methacrylate ester-tetraethylene glycol dimethacrylate copolymer **389104-93-2DP**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer 2-isocyanatoethyl methacrylate ester-N,N'-di(2-methacryloxyethyl)urea copolymer, reaction products with termination acids **389104-94-3P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer 2-isocyanatoethyl methacrylate ester-N,N'-di(2-methacryloxyethyl)urea-tetraethylene glycol dimethacrylate copolymer
(photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for **lithog.**

patterning containing them)

IT **389104-83-0P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, phthalic anhydride-terminated, ester with 2-isocyanatoethyl methacrylate **389104-84-1P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, terminated with methanesulfonyl chloride, carbamate ester with 2-isocyanatoethyl methacrylate **389104-85-2P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, terminated with p-toluenesulfonyl chloride, carbamate ester with 2-isocyanatoethyl methacrylate **389104-86-3P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, terminated with 5-norbornene-2,3-dicarboxylic anhydride, carbamate ester with 2-isocyanatoethyl methacrylate **389104-87-4P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, terminated with glutaric anhydride, carbamate ester with 2-isocyanatoethyl methacrylate **389104-89-6P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, terminated with di-tert-butyl carbonate, carbamate ester with 2-isocyanatoethyl methacrylate **389104-90-9P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, carbamate ester with 2-isocyanatoethyl methacrylate **389104-95-4P**, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer polyamide sru, terminated with cyclohexane-1,2-dicarboxylic anhydride, carbamate ester with 2-isocyanatoethyl methacrylate
(photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for **lithog.** patterning containing them)

IT 112480-82-7P 133440-72-9DP, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane-4,4'-diphenyl ether dicarboxylic acid dichloride copolymer, reaction products with termination acids 389077-92-3P 389077-94-5P 389077-95-6P 389077-97-8P 389077-99-0P 389078-01-7P 389078-02-8P
(photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for lithog. patterning containing them)

IT 17322-98-4
(photoinitiators; photo-sensitive polybenzoxazole **precursor** resins and alkali-developable compns. useful for lithog. patterning containing them)

L20 ANSWER 24 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2001:709715 HCAPLUS
DOCUMENT NUMBER: 135:264587
TITLE: Lithographic printing plate **precursor** comprising compounds with changable hydrophilicity under heat
INVENTOR(S): Oohashi, Hidekazu
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 110 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent

LANGUAGE: English
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1136281	A1	20010926	EP 2001-106393	20010320
EP 1136281	B1	20040121		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
JP 2001337460	A2	20011207	JP 2000-337792	20001106
US 2003190553	A1	20031009	US 2001-812053	20010320
US 6680161	B2	20040120		
EP 1371500	A1	20031217	EP 2003-21157	20010320
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, FI, CY, TR				
AT 258115	E	20040215	AT 2001-106393	20010320

PRIORITY APPLN. INFO.:	JP 2000-78597	A	20000321
	JP 2000-337792	A	20001106
	EP 2001-106393	A3	20010320

AB A lithog. printing plate **precursor** which comprises a support having a hydrophilic surface containing a latex A and an ink-receptive layer B whose solubility at least either in water or in an aqueous solution is converted by heat, wherein at least one layer of either layer A or layer B contains a light/heat converting agent. The object of the present invention is to provide a lithog. printing plate **precursor** developable with water or an aqueous solution, loadable on a printing machine without development after imaging and printable, which is improved in sensitivity and press life, and capable of providing clear printed matters having no residual colors and stains.

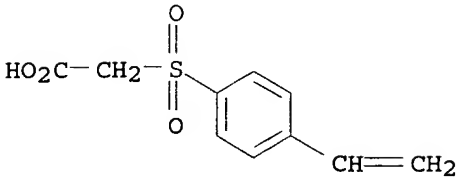
IT **265316-27-6 289893-00-1 289893-02-3**
(**lithog.** printing plate **precursor** comprising compds. with changable hydrophilicity under heat)

RN 265316-27-6 HCAPLUS

CN Acetic acid, [(4-ethenylphenyl)sulfonyl]-, homopolymer (9CI) (CA INDEX NAME)

CM 1

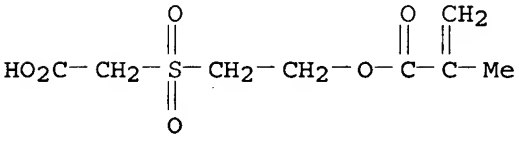
CRN 103945-08-0
CMF C10 H10 O4 S



RN 289893-00-1 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[(carboxymethyl)sulfonyl]ethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

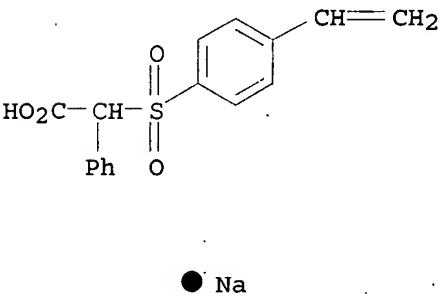
CRN 289892-99-5
CMF C8 H12 O6 S



RN 289893-02-3 HCAPLUS
CN Benzeneacetic acid, α-[(4-ethenylphenyl)sulfonyl]-, sodium salt, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 289893-01-2
CMF C16 H14 O4 S . Na



IC ICM B41N001-14
ICS B41C001-10; B41M005-36
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST lithog printing plate **precursor** compd heat induced changable hydrophilicity
IT Hydrophilicity

Lithographic plates
(lithog. printing plate **precursor** comprising compds. with changable hydrophilicity under heat)

IT 134127-48-3 289893-03-4 361542-00-9
(IR absorber; lithog. printing plate **precursor** comprising compds. with changable hydrophilicity under heat)

IT 55844-94-5P, Styrene-chloromethylstyrene-divinylbenzene copolymer 81876-52-0P, tert-Butyl methacrylate-ethylene glycol dimethacrylate copolymer 361486-95-5P
(lithog. printing plate **precursor** comprising compds. with changable hydrophilicity under heat)

IT 52858-60-3 215958-15-9 215958-19-3 **265316-27-6** 265316-42-5 265316-43-6 **289893-00-1** **289893-02-3**
(**lithog.** printing plate **precursor** comprising compds. with changable hydrophilicity under heat)

REFERENCE COUNT: 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L20 ANSWER 25 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2001:579379 HCAPLUS
DOCUMENT NUMBER: 135:173003
TITLE: Silver halide diffusion-transfer lithographic plate **precursor** having protecting layer on support
INVENTOR(S): Endo, Akihiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 34 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001215712	A2	20010810	JP 2000-25546	2000 0202

PRIORITY APPLN. INFO.: JP 2000-25546 2000 0202

AB The title printing plate **precursor** has a phys. development nuclei layer and a light-sensitive silver halide emulsion layer on an aluminum support, wherein the aluminum support has 0.1-10 mg/m2 Si atom adhered on the surface and a protecting layer made of a polymer having repeating units of onium groups and Ag coordinated groups. The materials, which has the controlled amount of Si on the support and the protecting layer on the support, provides the printing plate of the improved printing durability and the prevented soiling.

IT **214279-68-2 353456-37-8**
(protecting layer on support for silver halide diffusion-transfer **lithog.** plate **precursor**)

RN 214279-68-2 HCAPLUS
CN Benzenemethanaminium, ar-ethenyl-N,N,N-trimethyl-, chloride, polymer with 4-ethenylbenzoic acid (9CI) (CA INDEX NAME)

CM 1

CRN 26616-35-3
CMF C12 H18 N . Cl
CCI IDS

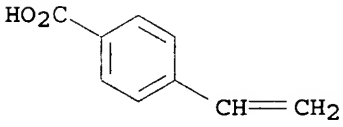
D1— CH═ CH_2

$Me_3{}^+N$— CH_2— D1

● Cl^-

CM 2

CRN 1075-49-6
CMF C9 H8 O2

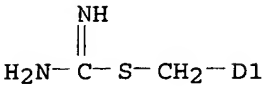


RN 353456-37-8 HCAPLUS
CN Benzenemethanaminium, ar-ethenyl-N,N,N-triethyl-, chloride, polymer with 4-ethenylbenzoic acid and (ethenylphenyl)methyl carbamimidothioate monohydrochloride (9CI) (CA INDEX NAME)

CM 1

CRN 87051-44-3
CMF C10 H12 N2 S . Cl H
CCI IDS

D1— CH═ CH_2



● HCl

CM 2

CRN 51241-16-8
CMF C15 H24 N . Cl
CCI IDS

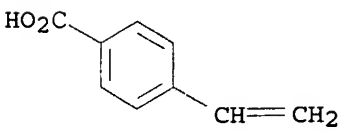
D1— CH═ CH_2

$Et_3{}^{+}N$— CH_2— D1

● Cl^-

CM 3

CRN 1075-49-6
CMF C9 H8 O2



IC ICM G03F007-07
ICS G03C008-06; G03F007-00; G03F007-11
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST silver halide complex diffusion transfer lithog plate **precursor**
IT Lithographic plates
Photographic emulsions
(silver halide diffusion-transfer lithog. plate **precursor** having protecting layer on support)
IT 7429-90-5, Aluminum, uses
(Silver halide diffusion-transfer lithog. plate **precursor** having protecting layer on support)
IT 1344-09-8, Sodium silicate
(Silver halide diffusion-transfer lithog. plate **precursor** having protecting layer on support)
IT 121448-09-7 **214279-68-2** 353456-34-5 353456-35-6
353456-36-7 **353456-37-8** 353456-38-9
(protecting layer on support for silver halide diffusion-transfer **lithog.** plate **precursor**)

L20 ANSWER 26 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2001:100796 HCAPLUS
DOCUMENT NUMBER: 134:170840
TITLE: Lithographic plates for writing by low-energy heat mode exposure
INVENTOR(S): Yamazaki, Sumiaki; Kawamura, Koichi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 42 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

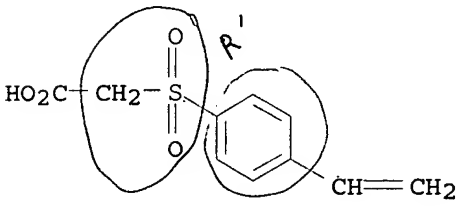
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001033949	A2	20010209	JP 2000-144823	2000 0517
PRIORITY APPLN. INFO.:			JP 1999-138776 A	1999 0519

AB The plate comprises a recording layer containing a 3-dimensionally crosslinked polymer layer having hydrophilic functional groups, which change into hydrophobic groups on irradiation of radiant beam or heat. Preferably, the polymer is a hydrolysis polymerization product of (a) compds. having the hydrophilic functional groups and ≥1 group(s) selected from OH, NH2, NHCOR3, and Si(OR4)3 (R3-4 = alkyl, aryl) and (b) R5nX1(OR6)4-n (R5-6 = alkyl, aryl; X1 = Si, Al, Ti, Zr; n = 0, 1, 2). The recording layer may also contain photo-thermal conversion substances, e.g. IR absorbers. The polymer may be crosslinked by application of light or heat. Images are formed on the plates by direct writing of digital information.
IT **324752-52-5P 324752-69-4P**
(heat mode exposure direct writing **lithog.** plates comprising of radiation- or **heat-sensitive**

hydrophilic crosslinked polymers)
RN 324752-52-5 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with [(4-ethenylphenyl)sulfonyl]acetic acid, silicic acid and silicic acid ethyl ester (9CI) (CA INDEX NAME)

CM 1

CRN 103945-08-0
CMF C10 H10 O4 S



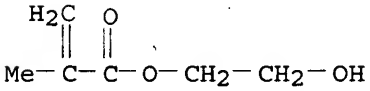
CM 2

CRN 1343-98-2
CMF Unspecified
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 3

CRN 868-77-9
CMF C6 H10 O3



CM 4

CRN 11099-06-2
CMF C2 H6 O . x Unspecified

CM 5

CRN 1343-98-2
CMF Unspecified
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

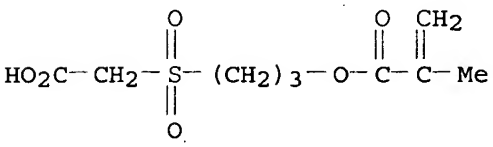
CM 6

CRN 64-17-5
CMF C2 H6 O

RN 324752-69-4 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 3-[(carboxymethyl)sulfonyl]propyl ester, polymer with silicic acid, silicic acid ethyl ester and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

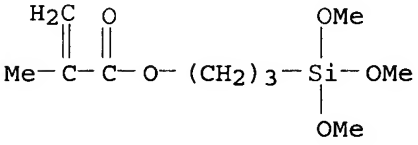
CM 1

CRN 265316-39-0
CMF C9 H14 O6 S



CM 2

CRN 2530-85-0
CMF C10 H20 O5 Si



CM 3

CRN 1343-98-2
CMF Unspecified
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 4

CRN 11099-06-2
CMF C2 H6 O . x Unspecified

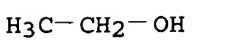
CM 5

CRN 1343-98-2
CMF Unspecified
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 6

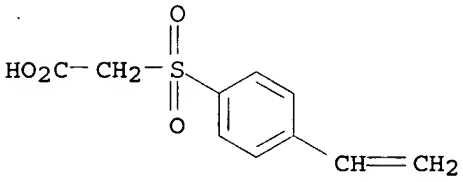
CRN 64-17-5
CMF C2 H6 O



IT **324747-77-5P**
(heat mode exposure direct writing **lithog.** plates comprising of radiation- or **heat-sensitive** hydrophilic crosslinked polymers)
RN 324747-77-5 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 3-(trimethoxysilyl)propyl ester, polymer with [(4-ethenylphenyl)sulfonyl]acetic acid (9CI) (CA INDEX NAME)

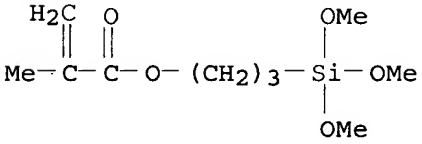
CM 1

CRN 103945-08-0
CMF C10 H10 O4 S



CM 2

CRN 2530-85-0
CMF C10 H20 O5 Si



IC ICM G03F007-00
ICS B41N001-14; G03F007-004; G03F007-075
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
IT Optical materials
(IR absorbers; heat mode exposure direct writing lithog. plates comprising of radiation- or **heat-sensitive** hydrophilic crosslinked polymers)
IT IR materials
(absorbers; heat mode exposure direct writing lithog. plates comprising of radiation- or **heat-sensitive** hydrophilic crosslinked polymers)
IT Ceramers

Lithographic plates
Photoimaging materials
(heat mode exposure direct writing lithog. plates comprising of radiation- or **heat-sensitive** hydrophilic crosslinked polymers)

IT Recording materials
(thermal; heat mode exposure direct writing lithog. plates comprising of radiation- or **heat-sensitive** hydrophilic crosslinked polymers)

IT 5496-71-9, IRG 022 22371-56-8, NK 3508
(IR absorber; heat mode exposure direct writing lithog. plates comprising of radiation- or **heat-sensitive** hydrophilic crosslinked polymers)

IT 324747-69-5P 324747-70-8P 324747-72-0P 324747-74-2P
324747-75-3P 324747-76-4P **324752-52-5P** 324752-53-6P
324752-55-8P 324752-56-9P 324752-58-1P 324752-61-6P
324752-63-8P 324752-66-1P 324752-67-2P 324752-68-3P
324752-69-4P
(heat mode exposure direct writing **lithog.** plates comprising of radiation- or **heat-sensitive** hydrophilic crosslinked polymers)

IT 324747-67-3P 324747-73-1P
(heat mode exposure direct writing lithog. plates comprising of radiation- or **heat-sensitive** hydrophilic crosslinked polymers)

IT **324747-77-5P**
(heat mode exposure direct writing **lithog.** plates comprising of radiation- or **heat-sensitive** hydrophilic crosslinked polymers)

IT 324747-78-6P
(heat mode exposure direct writing lithog. plates comprising of radiation- or **heat-sensitive** hydrophilic crosslinked polymers)

L20 ANSWER 27 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 1994:496062 HCAPLUS
DOCUMENT NUMBER: 121:96062
TITLE: Electrophotographic lithographic plate **precursor**
INVENTOR(S): Kato, Eiichi
PATENT ASSIGNEE(S): Fuji Photo Film Co Ltd, Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 98 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 05127393	A2	19930525	JP 1991-311312	1991 1031

PRIORITY APPLN. INFO.: JP 1991-311312 1991 1031

AB In the title **precursor** utilizing an electrophotog. photoreceptor made by forming on an elec. conductive support

≥1 photoconductive layer(s) and forming on the top layer a surface layer, the surface layer contains ≥1 kind(s) of the following nonaq. solvent-dispersed resin grains [L] and the photoconductive layer contains ≥1 kind(s) of the following resins [A] as a binder resin. The resin grains [L] are obtained in a nonaq. solvent by dispersion polymerization of ≥1 kind(s) of mono functional monomers (C) being soluble in the nonaq. solvent but insol. after polymerization and which contains ≥1 kind(s) of functional groups which forms ≥1 of SH, SO3H, amino, and P(:Z)(-Z-H)R1 groups [Z = O, S; R1 = -Z-H, hydrocarbon, -Z-R2 (R2 = hydrocarbon)] upon decomposition in the presence of a dispersion stabilizing polymer containing at least repeating units containing a substituent group(s) containing Si and/or F and soluble to the nonaq. solvent. The resins [A] are resins having a weight average mol. weight 1 x 103-2 x 104; the resins contain as a polymer component the repeating monomer units [-CHa1-Ca2(CO2R3)-] (a1, a2 = H, halo, CN, hydrocarbon group; R3 = hydrocarbon group) >30% and a polymer component 0.5-15 % having ≥1 kind of polar groups selected from -PO3H2, -SO3H, -CO2H, -P(:O)(OH)R1 [R1 = hydrocarbon group, OR2 (R2 = hydrocarbon group)], and cyclic acid anhydride-containing groups. The lithog. plate **precursor** provides superior printing images and shows high printing durability even under severe conditions and is effective for scanning exposure using a semiconductor laser.

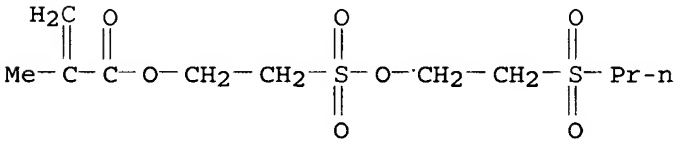
IT **155554-91-9P**
(latex, preparation and use of, for surface layer of electrophotog. **lithog.** plate **precursor**)

RN 155554-91-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,6-nonafluorohexyl ester, polymer with 2-carboxyethyl 2-propenoate, 1,2-ethanediyl di-2-propenoate and 2-[[2-(propylsulfonyl)ethoxy]sulfonyl]ethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

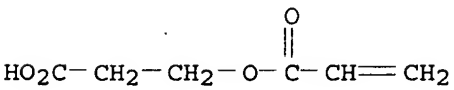
CM 1

CRN 149212-82-8
CMF C11 H20 O7 S2



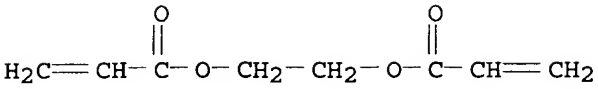
CM 2

CRN 24615-84-7
CMF C6 H8 O4



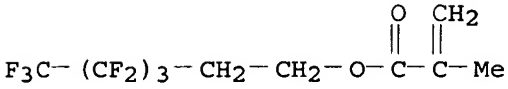
CM 3

CRN 2274-11-5
CMF C8 H10 O4



CM 4

CRN 1799-84-4
CMF C10 H9 F9 O2



IC ICM G03G005-05
ICS G03G005-147; G03G013-28
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT 149212-64-6P 149212-66-8P 149212-68-0P 149212-70-4P
149212-71-5P 149212-74-8P 149212-75-9P 149212-76-0P
149212-77-1P 149212-78-2P 149212-79-3P 149212-80-6P
149212-81-7P 149212-83-9P 149212-84-0P 149212-85-1P
149212-86-2P 149212-87-3P 149212-88-4P 149212-89-5P
149212-90-8P 149234-31-1P 149234-33-3P 149234-35-5P
149234-37-7P 149234-39-9P 149234-64-0P 149234-65-1P
149234-66-2P 149234-67-3P 149234-68-4P 149234-69-5P
149235-74-5P 149235-80-3P 149235-82-5P 149295-86-3P
149333-66-4P **155554-91-9P** 156321-46-9P 156622-62-7P
156705-17-8P
(latex, preparation and use of, for surface layer of electrophotog. **lithog.** plate **precursor**)

L20 ANSWER 28 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 1994:446534 HCAPLUS
DOCUMENT NUMBER: 121:46534
TITLE: Electrophotographic plate for electrophotographic lithographic plates
INVENTOR(S): Kato, Eiichi; Kasai, Seishi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: PCT Int. Appl., 213 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 9215048	A1	19920903	WO 1992-JP188	19920221

W: US
RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LU, MC, NL, SE

JP 04268564	A2	19920924	JP 1991-78711	1991 0222
JP 04291265	A2	19921015	JP 1991-78175	1991 0319
JP 04304462	A2	19921027	JP 1991-94886	1991 0402
JP 04355457	A2	19921209	JP 1991-156246	1991 0531
EP 535236	A1	19930407	EP 1992-905099	1992 0221
EP 535236	B1	19961218		
R: DE, GB				
US 5342716	A	19940830	US 1992-946320	1992 1022

PRIORITY APPLN. INFO.:	JP 1991-78711	A	1991 0222
	JP 1991-78175	A	1991 0319
	JP 1991-94886	A	1991 0402
	JP 1991-156246	A	1991 0531
	WO 1992-JP188	W	1992 0221

AB The title electrophotog. plate utilizing a photoconductor layer containing photoconductive ZnO, a spectral sensitizer dye, and a binder resin, the binder resin contains ≥1 resins (A) (weight average mol. weight 1 + 103-2 + 104) containing polymer component [CHa1a2(CO2R3)] [a1, a2 = H, halo, CN, hydrocarbon moiety; R3 = hydrocarbon moiety] ≥ 30% and a polymer component containing ≥1 polar groups selected from PO3H2, SO3H, CO2H, P(O)(OH)R1 (R1 = hydrocarbon or oxyhydrocarbon moiety), and a cyclic acid anhydride moiety 0.5-15%. In addition, the photoconductor layer contains nonaq. medium dispersed resin fine particles (L) having particle size less than that of the maximum diameter of the photoconductive ZnO particles utilized above. L is obtained by copolymg. a monofunctional monomer possessing ≥1 functional groups capable of decomposing to form CO2H with another monofunctional monomer(s) in the **precursor** of a nonaq. solvent-soluble dispersion-stabilizing resin with structure repeating units containing F- and(or) Si-containing substituents. The electrophotog. plate gives lithog. printing plates giving superior

printed copies even under severe ambient conditions and having good durability.

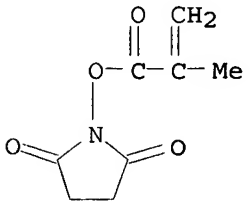
IT **149072-56-0**
(latex particles, for electrophotog. **lithog.** plates)

RN 149072-56-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,6-nonafluorohexyl ester, polymer with 2-carboxyethyl 2-propenoate, 1,2-ethanediyl di-2-propenoate and 1-[(2-methyl-1-oxo-2-propenyl)oxy]-2,5-pyrrolidinedione, graft (9CI) (CA INDEX NAME)

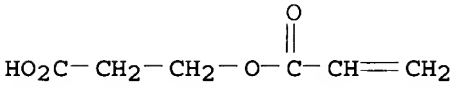
CM 1

CRN 38862-25-8
CMF C8 H9 N O4



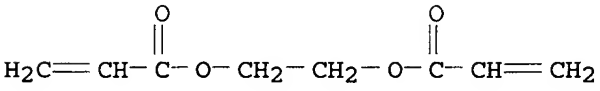
CM 2

CRN 24615-84-7
CMF C6 H8 O4



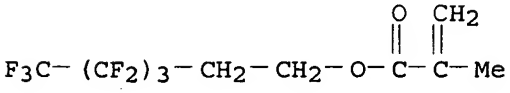
CM 3

CRN 2274-11-5
CMF C8 H10 O4



CM 4

CRN 1799-84-4
CMF C10 H9 F9 O2

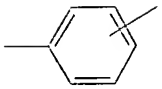


IC ICM G03G005-05
CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35
IT 149072-29-7 149072-31-1 149072-33-3 149072-34-4
149072-35-5 149072-36-6 149072-38-8 149072-39-9
149072-40-2 149072-41-3 149072-42-4 149072-43-5
149072-44-6 149072-45-7 149072-46-8 149072-47-9
149072-48-0 149072-49-1 149072-50-4 149072-51-5
149072-52-6 149072-53-7 149072-55-9 **149072-56-0**
149072-57-1 149072-58-2 149072-59-3 149072-61-7
149072-62-8 149072-63-9 149072-98-0 149072-99-1
149093-43-6 149093-44-7 149093-45-8 149093-46-9
149093-47-0 149093-48-1 149093-50-5 149093-51-6
149093-53-8 149093-58-3 149124-86-7 149333-75-5
150497-83-9 150497-84-0 150497-86-2 150497-88-4
150497-96-4
(latex particles, for electrophotog. **lithog.** plates)

L20 ANSWER 29 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 1994:422526 HCAPLUS
DOCUMENT NUMBER: 121:22526
TITLE: lithographic plate **precursor** of direct image type
INVENTOR(S): Kato, Eiichi; Ishii, Kazuo
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 127 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 530957	A1	19930310	EP 1992-306370	1992 0710
EP 530957 R: DE, GB	B1	19991222		
US 5368931	A	19941129	US 1992-910968	1992 0709
PRIORITY APPLN. INFO.:			JP 1991-169828 A	1991 0710
			JP 1991-220275 A	1991 0830
			JP 1991-231880 A	1991 0911

GI



I

AB The title **precursor** comprises a base and an image-receptive layer containing resin grains obtained by subjecting to dispersion polymerization in an organic solvent a monofunctional monomer which is soluble in the solvent but is insol. after polymerization and contains ≥1 functional group capable of producing ≥1 polar group through decomposition and a monofunctional polymer comprising a polymer chain containing ≥1 recurring unit each containing a Si- and/or F-containing substituent and bonded to one end a polymerizable double bond group represented by the formula CHA1:CA2V- (V = O, CO2, OCO, CH2OCO, CH2CO2, SO2, CONR1, SO2NR1, CONCHCO2, CONHCONH, or I; R1 = H or C1-18 hydrocarbyl; A1, A2 = H, halogen, cyano, hydrocarbyl, or CO2R2; R2 = H or hydrocarbyl).

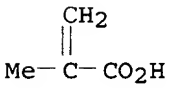
IT **149368-85-4P 149434-28-6P**
(preparation and copolymn. of, in preparing latexes for **lithog** . plate **precursors**)

RN 149368-85-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,6-nonafluorohexyl ester, telomer with 2-carboxyethyl 2-propenoate and 2-mercaptoethanol, 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 79-41-4
CMF C4 H6 O2

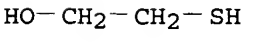


CM 2

CRN 163148-87-6
CMF (C10 H9 F9 O2 . C6 H8 O4)x . C2 H6 O S

CM 3

CRN 60-24-2
CMF C2 H6 O S

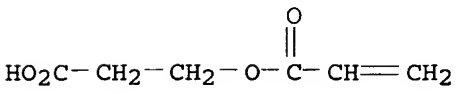


CM 4

CRN 163148-86-5
CMF (C10 H9 F9 O2 . C6 H8 O4)x
CCI PMS

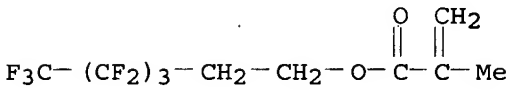
CM 5

CRN 24615-84-7
CMF C6 H8 O4



CM 6

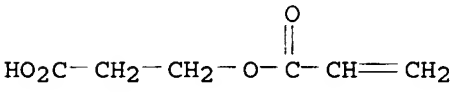
CRN 1799-84-4
CMF C10 H9 F9 O2



RN 149434-28-6 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, telomer with 2-mercaptoethanol and phenylbis(trifluoromethyl)silyl 2-methyl-2-propenoate, 3-[(1-oxo-2-propenyl)oxy]propanoate (9CI) (CA INDEX NAME)

CM 1

CRN 24615-84-7
CMF C6 H8 O4

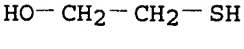


CM 2

CRN 163255-66-1
CMF (C12 H10 F6 O2 Si . C4 H6 O2)x . C2 H6 O S

CM 3

CRN 60-24-2
CMF C2 H6 O S

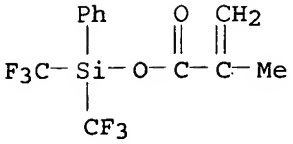


CM 4

CRN 163255-65-0
CMF (C12 H10 F6 O2 Si . C4 H6 O2)x
CCI PMS

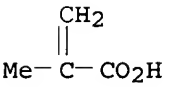
CM 5

CRN 149072-54-8
CMF C12 H10 F6 O2 Si



CM 6

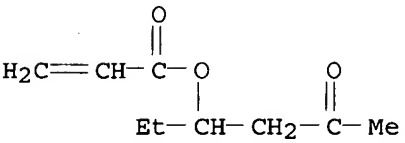
CRN 79-41-4
CMF C4 H6 O2



IT **155554-40-8P 155554-91-9P**
(preparation and use of, in image-receptive layers for **lithog.** plate **precursors**)
RN 155554-40-8 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 1,2-ethanediyl ester, polymer with 2-carboxyethyl 2-propenoate, 1-ethyl-3-oxobutyl 2-propenoate and 3,3,4,4,5,5,6,6,6-nonafluorohexyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

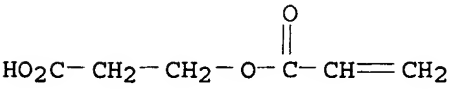
CM 1

CRN 155554-39-5
CMF C9 H14 O3



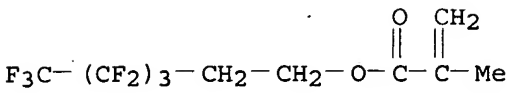
CM 2

CRN 24615-84-7
CMF C6 H8 O4



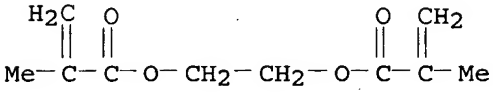
CM 3

CRN 1799-84-4
CMF C10 H9 F9 O2



CM 4

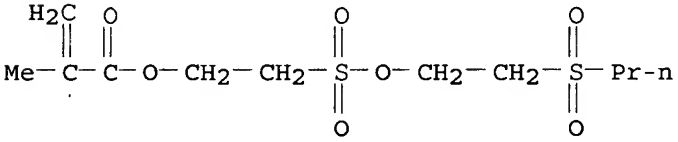
CRN 97-90-5
CMF C10 H14 O4



RN 155554-91-9 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,6-nonafluorohexyl ester, polymer with 2-carboxyethyl 2-propenoate, 1,2-ethanediyl di-2-propenoate and 2-[[2-(propylsulfonyl)ethoxy]sulfonyl]ethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

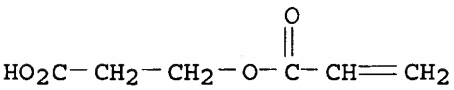
CM 1

CRN 149212-82-8
CMF C11 H20 O7 S2



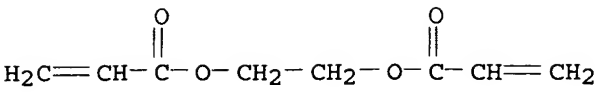
CM 2

CRN 24615-84-7
CMF C6 H8 O4



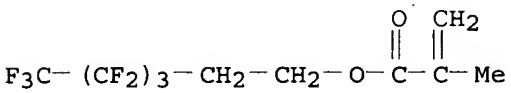
CM 3

CRN 2274-11-5
CMF C8 H10 O4



CM 4

CRN 1799-84-4
CMF C10 H9 F9 O2



IC ICM G03F007-033
ICS B41N001-14
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST lithog plate **precursor** rein grain
IT Fluoropolymers
(image-receptive layers containing polymer latexes and, for lithog. plate **precursors**)
IT Lithographic plates
(**precursors**, direct image type, image-receptive layers containing polymer resin grains for)
IT Siloxanes and Silicones, uses
(methacrylate-terminated, preparation and use of, in image-receptive layers for lithog. plate **precursors**)
IT 25322-25-2, Acrylic acid-methyl methacrylate copolymer 155555-00-3 155555-01-4
(image-receptive layers containing polymer latexes and, for lithog. plate **precursors**)
IT 145168-75-8P 145168-89-4P 145168-94-1P 145169-02-4P
145169-03-5P 145169-04-6P 145169-24-0P 145169-26-2P
145169-30-8P 145807-38-1P 145807-40-5P 145807-41-6P
145807-51-8P 145807-53-0P 145807-54-1P 145807-55-2P
145807-56-3P 145807-57-4P 145807-63-2P 145807-64-3P
145807-65-4P 145807-66-5P 145807-68-7P 145807-70-1P
145807-71-2P 145807-72-3P 145807-78-9P 145807-80-3P
146188-26-3DP, carboxy-terminated, ester with 2-hydroxyethyl methacrylate 147545-76-4P 149072-24-2DP, reaction products with 2-isocyanatoethyl methacrylate 149368-83-2P
149368-85-4P 149434-15-1P 149434-21-9P 149434-25-3P
149434-28-6P 149434-33-3P 149658-55-9P
(preparation and copolymn. of, in preparing latexes for **lithog**. plate **precursors**)
IT 2358-84-1DP, Diethylene glycol dimethacrylate, polymers with methacrylate-terminated siloxanes and methacrylates 78830-72-5DP, polymers with methacrylate-terminated siloxanes and methacrylates 149212-88-4P 149234-31-1P 150372-99-9P
150373-00-5P 150373-02-7P 150373-03-8P 150373-06-1P
150373-07-2P 150373-08-3P 150391-01-8P 150391-02-9P
150391-87-0P 150419-15-1P 150528-35-1P 150958-52-4P
150997-02-7P 155554-20-4P 155554-21-5P 155554-22-6P
155554-23-7P 155554-24-8P 155554-25-9P 155554-26-0P
155554-27-1P 155554-28-2P 155554-29-3P 155554-30-6P

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155554-40-8P 155554-41-9P 155554-42-0P 155554-43-1P
155554-44-2P 155554-45-3P 155554-46-4P 155554-47-5P
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155554-75-9P 155554-76-0P 155554-77-1P 155554-78-2P
155554-79-3P 155554-80-6P 155554-81-7P 155554-82-8P
155554-83-9P 155554-84-0P 155554-85-1P 155554-86-2P
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155554-91-9P 155554-92-0P 155554-93-1P 155554-94-2P
155554-95-3P 155554-96-4P 155554-97-5P 155554-98-6P
155554-99-7P 155569-64-5P 155609-29-3P 155616-65-2P
155643-92-8P 155643-93-9P
(preparation and use of, in image-receptive layers for **lithog.** plate **precursors**)

L20 ANSWER 30 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 1994:120660 HCAPLUS
DOCUMENT NUMBER: 120:120660
TITLE: Electrophotographic lithographic master
INVENTOR(S): Kato, Eiichi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 64 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

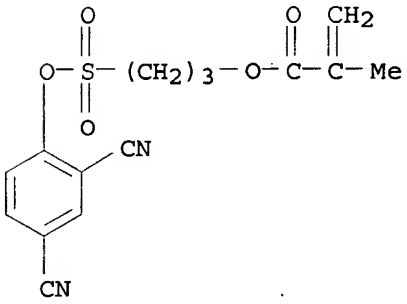
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 04366848	A2	19921218	JP 1991-142064	19910613
JP 2813078	B2	19981022		
PRIORITY APPLN. INFO.:			JP 1991-142064	19910613

AB In the title master comprising an elec. conductive support having thereon ≥1 photoconductive layers containing photoconductive zinc oxide, spectral sensitizing dye, and binder resin, said binder resin contains resin (A). Resin (A) (weight average mol. weight 1.0 + 103-2 + 104) has (CHA1CA2CO2R) (A1, A2 = H, halo, cyano, hydrocarbon; R = hydrocarbon) as a repeating unit. Resin (A) is terminated at one end of the backbone chain with ≥1 polar groups selected from PO3H2, SO3H, CO2H, etc. Said photoconductive layers addnl. contain nonaq. solvent-dispersed resin particles whose size is equal to or smaller than that of the ZnO particles. The above nonaq. solvent-dispersed resin particles are obtained by dispersing and polymerizing ≥1 monofunctional monomers (containing ≥1 **precursors** of groups such as thiol, amino, phosphono, etc.) in the presence of a soluble dispersion-stabilizing resin.

IT **149235-49-4P**
(preparation of, as resin for electrophotog. **lithog.** master)
RN 149235-49-4 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 1,2-ethanediyl ester, polymer with 2-carboxyethyl 2-propenoate, 3-[(2,4-dicyanophenoxy)sulfonyl]propyl 2-methyl-2-propenoate and pentyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

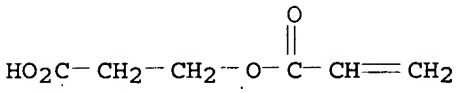
CM 1

CRN 149234-43-5
CMF C15 H14 N2 O5 S



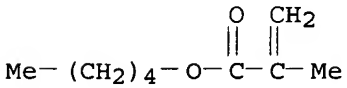
CM 2

CRN 24615-84-7
CMF C6 H8 O4



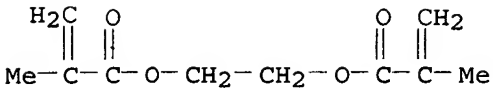
CM 3

CRN 2849-98-1
CMF C9 H16 O2



CM 4

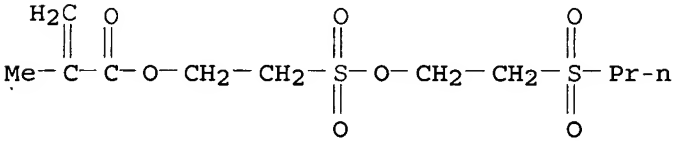
CRN 97-90-5
CMF C10 H14 O4



IT **149235-66-5P**
(preparation of, for electrophotog. **lithog.** master)
RN 149235-66-5 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, pentyl ester, polymer with 2-carboxyethyl 2-propenoate, 1,2-ethanediyl di-2-propenoate and 2-[[2-(propylsulfonyl)ethoxy]sulfonyl]ethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

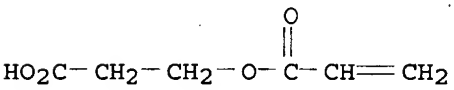
CM 1

CRN 149212-82-8
CMF C11 H20 O7 S2



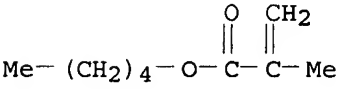
CM 2

CRN 24615-84-7
CMF C6 H8 O4



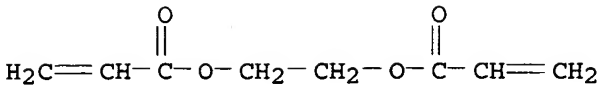
CM 3

CRN 2849-98-1
CMF C9 H16 O2



CM 4

CRN 2274-11-5
CMF C8 H10 O4



IC ICM G03G005-05
ICS G03G005-06; G03G013-28
CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT 149235-48-3P **149235-49-4P** 149235-51-8P 149235-53-0P
149235-54-1P 149235-55-2P 149235-56-3P 149235-57-4P
149235-58-5P 149275-09-2P 149275-10-5P
(preparation of, as resin for electrophotog. **lithog.** master)
IT 25719-51-1DP, carboxy-terminated, ester with 2-hydroxyethyl methacrylate, polymer with ethyleneglycol di-acrylate and methacrylic acid ester 149235-60-9P 149235-61-0P
149235-62-1P 149235-63-2P 149235-64-3P 149235-65-4P
149235-66-5P 149235-67-6P 149235-68-7P 149235-69-8P
149235-70-1P 149235-71-2P 149235-73-4P 149235-84-7P
149275-11-6P 149275-12-7P 149476-82-4P 149478-77-3P
149512-89-0P 149512-92-5P 149512-93-6P 149512-94-7P
149512-95-8P 149512-96-9P 149512-97-0P 149512-98-1P
149512-99-2P 149544-80-9P
(preparation of, for electrophotog. **lithog.** master)

L20 ANSWER 31 OF 31 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 1993:549517 HCAPLUS
DOCUMENT NUMBER: 119:149517
TITLE: Electrophotographic plate for lithographic plate preparation
INVENTOR(S): Kato, Eiichi; Ishii, Kazuo
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 52 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 04251861	A2	19920908	JP 1991-26850	19910128
JP 3048178	B2	20000605		

PRIORITY APPLN. INFO.: JP 1991-26850 19910128

AB In the title electrophotog. plate employing ≥1 photoconductive layer containing photoconductive ZnO and a binder resin, the binder resin contains ≥1 resin (weight-average mol. weight 1 + 103-2 + 104) containing the repeating unit CHa1Ca2(CO2R) [a1, a2 = H, halo, CN, hydrocarbon moiety; R = hydrocarbon moiety] ≥30% and a polymer component containing groups selected from PO3H2, SO3H, CO2H, PO(OH)R1 (R1 = hydrocarbon moiety, oxyhydrocarbon moiety), and acid anhydride groups 0.5-15%

and the photoconductive layer addnl. contains nonaq. solvent-dispersed resin particles of particle size equal to or less than that of the ZnO particles. The above nonaq. solvent-dispersed resin particles are obtained by dispersion polymerizing ≥1 monofunctional monomer containing ≥1 CO2H **precursor** in the presence of a soluble dispersion-stabilizing resin.

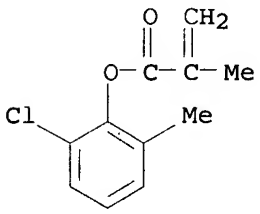
IT **130094-33-6P 135740-33-9P 135740-39-5P**
(preparation of, as binder resin, for electrophotog. **lithog** . plates)

RN 130094-33-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-chloro-6-methylphenyl ester, polymer with 2-carboxyethyl 2-propenoate (9CI) (CA INDEX NAME)

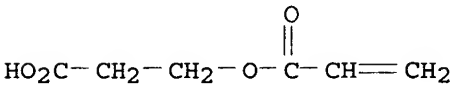
CM 1

CRN 126969-77-5
CMF C11 H11 Cl O2



CM 2

CRN 24615-84-7
CMF C6 H8 O4

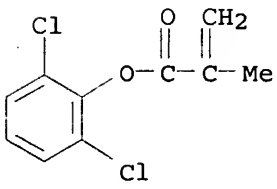


RN 135740-33-9 HCAPLUS

CN Benzoic acid, 4-ethenyl-, polymer with 2,6-dichlorophenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

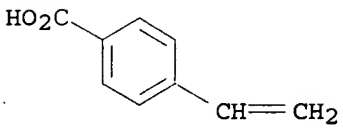
CM 1

CRN 126969-69-5
CMF C10 H8 Cl2 O2



CM 2

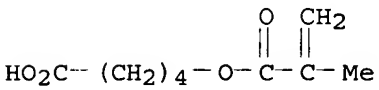
CRN 1075-49-6
CMF C9 H8 O2



RN 135740-39-5 HCAPLUS
CN Pentanoic acid, 5-[(2-methyl-1-oxo-2-propenyl)oxy]-, polymer with 2-naphthalenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

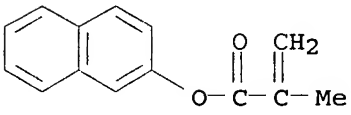
CM 1

CRN 73903-37-4
CMF C9 H14 O4



CM 2

CRN 10475-46-4
CMF C14 H12 O2



IC ICM G03G005-05
ICS C08K003-22; C08L101-00; G03G005-08; G03G013-28
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT 65697-21-4P 65697-22-5P 126969-70-8P 126969-78-6P
130094-33-6P 130952-79-3P 131808-63-4P 135740-30-6P
135740-31-7P 135740-32-8P **135740-33-9P** 135740-35-1P
135740-36-2P 135740-37-3P 135740-38-4P **135740-39-5P**
135740-41-9P 135740-43-1P 135740-44-2P 135740-46-4P
135770-63-7P 135820-62-1P 139663-63-1P 142648-25-7P
146817-57-4P 146817-58-5P 146817-60-9P 146817-61-0P
(preparation of, as binder resin, for electrophotog. **lithog** . plates)